

=> d his ful

(FILE 'HOME' ENTERED AT 07:14:01 ON 04 NOV 2008)

FILE 'REGISTRY' ENTERED AT 07:14:13 ON 04 NOV 2008  
E C11H12O2S/MF

L1 808 SEA ABB=ON PLU=ON C11H12O2S/MF  
L2 2198987 SEA ABB=ON PLU=ON ?SULFONYL?/CNS  
L3 84 SEA ABB=ON PLU=ON L1 AND L2

FILE 'STNGUIDE' ENTERED AT 07:23:56 ON 04 NOV 2008  
D SCA

FILE 'REGISTRY' ENTERED AT 07:33:30 ON 04 NOV 2008  
D SCA

FILE 'LREGISTRY' ENTERED AT 07:38:06 ON 04 NOV 2008

L4 137 SEA ABB=ON PLU=ON L1 AND ?BENZENE?/CNS  
D SCA  
SET LINE 250  
SET DETAIL OFF  
SET LINE LOGIN  
SET DETAIL LOGIN  
L5 38 SEA ABB=ON PLU=ON L1 AND ?ETHENYL?/CNS  
D SCA  
L6 0 SEA ABB=ON PLU=ON L1 AND PMS/CI  
L7 387 SEA ABB=ON PLU=ON L1 AND 1/NR  
E C10H12O3S/MF  
L8 145 SEA ABB=ON PLU=ON C10H12O3S/MF AND ?SULFONYL?/CNS  
L9 8 SEA ABB=ON PLU=ON L8 AND ?ETHANOL?/CNS  
L10 25496 SEA ABB=ON PLU=ON ?ETHENYLPHENYL?/CNS  
L11 2 SEA ABB=ON PLU=ON L10 AND L9  
D L11 1-2 STR RN  
L12 2 SEA ABB=ON PLU=ON 700870-27-5/CRN  
L13 2 SEA ABB=ON PLU=ON L12 AND PMS/CI  
SAV L13 TEMP CHO333A/A

FILE 'HCAPLUS' ENTERED AT 09:05:16 ON 04 NOV 2008

L14 2 SEA ABB=ON PLU=ON L13  
D L14 TI AU  
D L14 1-2 TI AU  
S PMS/CI

FILE 'REGISTRY' ENTERED AT 09:06:22 ON 04 NOV 2008

L15 1240717 SEA ABB=ON PLU=ON PMS/CI

FILE 'REGISTRY' ENTERED AT 09:39:32 ON 04 NOV 2008

E C10H11O2CL/MF

E C10H11CLO2/MF

L16 0 SEA ABB=ON PLU=ON C10H11CLO2/MF AND ?SULFONYL?/CNS  
L17 16 SEA ABB=ON PLU=ON C10H11CLO2/MF AND ?ETHENYL?/CNS  
D SCA  
L18 208 SEA ABB=ON PLU=ON C10H11CLO2/MF AND ?BENZENE?/CNS  
L19 20 SEA ABB=ON PLU=ON L18 AND ?CHLORIDE?/CNS  
D SCA  
L20 190 SEA ABB=ON PLU=ON L18 AND ?CHLORO?/CNS  
L21 16 SEA ABB=ON PLU=ON C10H11CLO2/MF AND (?CHLORO? AND  
?ETHENYL?) /CNS  
D L21  
D SCA L21  
D SCA L18

FILE 'LREGISTRY' ENTERED AT 10:34:50 ON 04 NOV 2008

L22 STR

FILE 'REGISTRY' ENTERED AT 10:39:14 ON 04 NOV 2008

L23 10 SEA SSS SAM L22  
D QUE STAT  
L24 STR L22  
L25 8 SEA SSS SAM L24  
STR L24  
L26 3 SEA SSS SAM L26  
D QUE STAT L25

FILE 'LREGISTRY' ENTERED AT 10:59:34 ON 04 NOV 2008

L28 STR L22  
L29 STR L24

FILE 'REGISTRY' ENTERED AT 11:00:28 ON 04 NOV 2008

L30 2 SEA SSS SAM L29

FILE 'LREGISTRY' ENTERED AT 11:02:46 ON 04 NOV 2008

L31 STR L24

FILE 'REGISTRY' ENTERED AT 11:03:16 ON 04 NOV 2008

L32 8 SEA SSS SAM L31  
D QUE STAT  
SAV TEMP L24 CHO258B/Q  
L33 STR L24  
L34 8 SEA SSS SAM L33

L35 182 SEA SSS FUL L33

FILE 'HCAPLUS' ENTERED AT 11:23:18 ON 04 NOV 2008

L36 106 SEA ABB=ON PLU=ON L35  
SAV TEMP L36 CHO333D/A

L37 0 SEA ABB=ON PLU=ON L36 AND PY<=2002 NOT P/DT

L38 66 SEA ABB=ON PLU=ON L36 AND (PD<=20021127 OR PRD20021127  
OR AD<=20021127) AND P/DT

FILE 'REGISTRY' ENTERED AT 11:52:07 ON 04 NOV 2008

L39 142 SEA ABB=ON PLU=ON L35 AND PMS/CI

FILE 'HCAPLUS' ENTERED AT 11:52:31 ON 04 NOV 2008

L40 103 SEA ABB=ON PLU=ON L39

L41 0 SEA ABB=ON PLU=ON L40 AND PY<=2002 NOT P/DT

L42 65 SEA ABB=ON PLU=ON L40 AND (PD<=20021127 OR PRD20021127  
OR AD<=20021127) AND P/DT

FILE 'REGISTRY' ENTERED AT 11:54:29 ON 04 NOV 2008

FILE HOME

FILE REGISTRY

Property values tagged with IC are from the ZIC/VINITI data file  
provided by InfoChem.

STRUCTURE FILE UPDATES: 2 NOV 2008 HIGHEST RN 1070028-20-4

DICTIONARY FILE UPDATES: 2 NOV 2008 HIGHEST RN 1070028-20-4

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH July 5, 2008.

Please note that search-term pricing does apply when  
conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and  
predicted properties as well as tags indicating availability of  
experimental property data in the original document. For information  
on property searching in REGISTRY, refer to:

<http://www.cas.org/support/stngen/stndoc/properties.html>

FILE STNGUIDE

FILE CONTAINS CURRENT INFORMATION.

LAST RELOADED: Oct 31, 2008 (20081031/UP).

FILE LREGISTRY  
LREGISTRY IS A STATIC LEARNING FILE

NEW CAS INFORMATION USE POLICIES, ENTER HELP USAGETERMS FOR DETAILS.

FILE HCAPLUS

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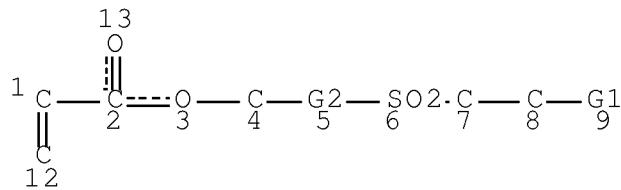
FILE COVERS 1907 - 4 Nov 2008 VOL 149 ISS 19  
FILE LAST UPDATED: 3 Nov 2008 (20081103/ED)

HCAplus now includes complete International Patent Classification (I reclassification data for the second quarter of 2008.

New CAS Information Use Policies, enter HELP USAGETERMS for details.

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> d que stat 133  
L33 STR



VAR G1=O/X  
VAR G2=AK/ID  
NODE ATTRIBUTES:  
DEFAULT MLEVEL IS ATOM  
DEFAULT ECLEVEL IS LIMITED

## GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED  
 NUMBER OF NODES IS 11

STEREO ATTRIBUTES: NONE

L14 ANSWER 1 OF 2 HCPLUS COPYRIGHT 2008 ACS on STN  
 AN 2005:1256466 HCPLUS Full-text  
 DN 144:151884  
 TI Latent reactive groups unveiled through equilibrium dynamics and exemplified in crosslinking during film formation from aqueous polymer colloids  
 AU Berrisford, David J.; Lovell, Peter A.; Suliman, Nadia R.; Whiting, Andrew  
 CS School of Chemistry, University of Manchester, Manchester, M60 1QD, UK  
 SO Chemical Communications (Cambridge, United Kingdom) (2005), (47), 5904-5906  
 CODEN: CHCOFS; ISSN: 1359-7345  
 PB Royal Society of Chemistry  
 DT Journal  
 LA English  
 OS CASREACT 144:151884  
 AB The concept of using equilibrium dynamics to provide for both protection and unveiling of latent functional groups at appropriate times in aqueous polymer latex coatings designed for crosslinking only during film formation is introduced. New functional monomers including 4-hydroxyethylsulfonylstyrene (HESS) were prepared HESS undergoes emulsion copolyrn. with acrylates to form stable latexes, followed by crosslinking by loss of water during film formation.  
 CC 42-10 (Coatings, Inks, and Related Products)  
 Section cross-reference(s): 35  
 IT 56793-24-9P 132099-67-3P 700871-52-9P  
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)  
 (latent reactive groups unveiled through equilibrium dynamics and exemplified in crosslinking during film formation from aqueous polymer latex)  
 IT 700871-51-8P  
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)  
 (monomer; latent reactive groups unveiled through equilibrium

dynamics

and exemplified in crosslinking during film formation from aqueous polymer latex)

IT 700871-52-9P

RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)

(latent reactive groups unveiled through equilibrium dynamics and exemplified in crosslinking during film formation from aqueous polymer latex)

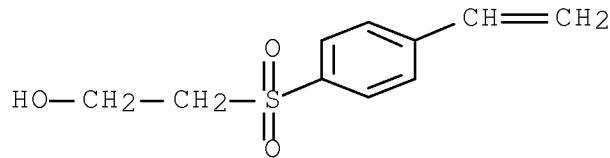
RN 700871-52-9 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with butyl 2-propenoate, 2-[(4-ethenylphenyl)sulfonyl]ethanol and 1,2-propanediol mono(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 700870-27-5

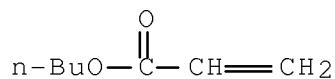
CMF C10 H12 O3 S



CM 2

CRN 141-32-2

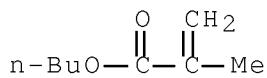
CMF C7 H12 O2



CM 3

CRN 97-88-1

CMF C8 H14 O2



CM 4

CRN 27813-02-1

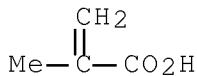
CMF C7 H12 O3

CCI IDS

CM 5

CRN 79-41-4

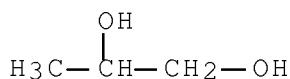
CMF C4 H6 O2



CM 6

CRN 57-55-6

CMF C3 H8 O2



IT 700871-51-8P

RL: PRP (Properties); SPN (Synthetic preparation); PREP  
(Preparation)

(monomer; latent reactive groups unveiled through equilibrium

dynamics

and exemplified in crosslinking during film formation from aqueous polymer latex)

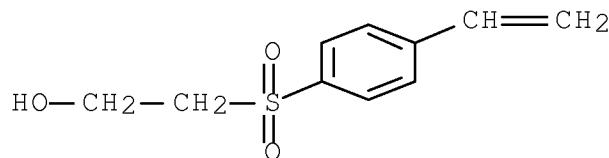
RN 700871-51-8 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with 2-[ (4-ethenylphenyl)sulfonyl]ethanol and 1,2-propanediol mono(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 700870-27-5

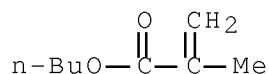
CMF C10 H12 O3 S



CM 2

CRN 97-88-1

CMF C8 H14 O2



CM 3

CRN 27813-02-1

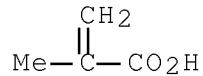
CMF C7 H12 O3

CCI IDS

CM 4

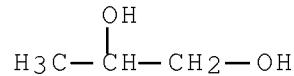
CRN 79-41-4

CMF C4 H6 O2



CM 5

CRN 57-55-6  
 CMF C3 H8 O2



## RETABLE

Referenced Author Referenced (RAU)	Year	VOL	PG	Referenced Work (RWK)	File
<hr/>					
Berrisford, D	2004	1	1	PCT/GB2003/005240	
Biswas, G	1991	21	569	Synth Commun	HCAPLUS
Brzezinska, K	2000	138	1544	J Polym Sci, Part A:	HCAPLUS
Cheng, W	2001	166	15528	J Org Chem	HCAPLUS
Cheng, W	2002	167	14387	J Org Chem	HCAPLUS
Cheng, W	2002	14	1741	Org Lett	HCAPLUS
Connors, R	2002	143	16661	Tetrahedron Lett	HCAPLUS
Guyot, A	2002	127	11573	Prog Polym Sci	HCAPLUS
Howard, J	1996	1	1796	Chem Ind	HCAPLUS
Jiang, L	1998	136	1347	Dyes Pigm	HCAPLUS
Kamogawa, H	1979	152	13010	Bull Chem Soc Jpn	HCAPLUS
Kamogawa, H	1983	156	1762	Bull Chem Soc Jpn	HCAPLUS
Kamogawa, H	1976	1	1419	Chem Lett	HCAPLUS
Katti, S	1992	1	1843	J Chem Soc, Chem Com	HCAPLUS
Khan, A	2000	130	12599	Synth Commun	HCAPLUS
Kong, K	2004	6	1928	J Comb Chem	HCAPLUS
Kroll, F	1997	138	18573	Tetrahedron Lett	HCAPLUS
Lovell, P	1997	1	1239	Emulsion Polymerizat	

Matloka, P	2005	206	218	Macromol Chem Phys	HCAPLUS
Pathak, T	2004	1	13361	Eur J Org Chem	HCAPLUS
Rowan, S	2002	41	1898	Angew Chem, Int Ed	
Taylor, J	2004	11	1163	JCT Res	HCAPLUS
Wade, W	2000	2	1266	J Comb Chem	HCAPLUS
Zhao, D	2002	124	19996	J Am Chem Soc	HCAPLUS
Zhu, Z	1991	17	1171	Dyes Pigm	HCAPLUS
Zhu, Z	1991	17	1217	Dyes Pigm	HCAPLUS
Zhu, Z	1998	36	1355	Dyes Pigm	HCAPLUS
Zohdy, M	1997	55	1185	Polym Degrad Stab	HCAPLUS

L14 ANSWER 2 OF 2 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2004:467946 HCAPLUS Full-text

DN 141:24550

TI Method for crosslinking of resin and crosslinkable resin compositions with improved storage stability

IN Lovell, Peter Alfred; Berrisford, David John; Whiting, Andrew

PA University of Manchester Institute of Science and Technology, UK

SO PCT Int. Appl., 33 pp.

CODEN: PIXXD2

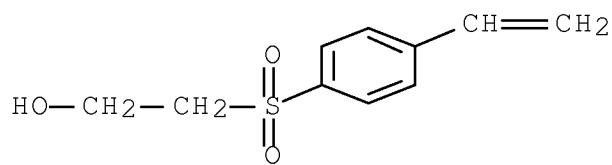
DT Patent

LA English

FAN.CNT 1

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PI	WO 2004048448	A1	20040610	WO 2003-GB5240	200311 27
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW:	BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU	2003290220	A1	20040618	AU 2003-290220	200311 27
EP	1565513	A1	20050824	EP 2003-782583	200311 27

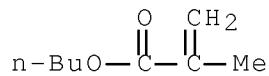
EP 1565513 B1 20080709  
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 PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU,  
 SK  
 AT 400604 T 20080715 AT 2003-782583  
200311  
27  
 US 20060009572 A1 20060112 US 2005-535333  
200508  
09  
 PRAI GB 2002-27608 A 20021127  
 WO 2003-GB5240 W 20031127  
 AB The method of effecting crosslinking of a resin comprises generating vinyl sulfonyl moieties in situ with the resin, the sulfonyl moieties then undergoing a reaction which effects crosslinking of the resin. The crosslinkable resin composition comprises a polymer to be crosslinked, a liquid carrier for the polymer, nucleophilic groups and the vinyl sulfonyl precursor group capable of generating vinyl sulfonyl groups on loss of liquid carrier from the composition. The crosslinking reaction results from reaction of the vinyl sulfonyl moieties with nucleophilic groups in the resin composition  
 IC ICM C08J003-00  
 ICS C08J003-24  
 CC 37-6 (Plastics Manufacture and Processing)  
 IT 700871-51-8 700871-52-9  
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
 (crosslinkable resin compns. containing vinyl sulfonyl precursor groups with improved storage stability)  
 IT 700871-51-8 700871-52-9  
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
 (crosslinkable resin compns. containing vinyl sulfonyl precursor groups with improved storage stability)  
 RN 700871-51-8 HCPLUS  
 CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with 2-[(4-ethenylphenyl)sulfonyl]ethanol and 1,2-propanediol mono(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)  
 CM 1  
 CRN 700870-27-5  
 CMF C10 H12 O3 S



CM 2

CRN 97-88-1

CMF C8 H14 O2



CM 3

CRN 27813-02-1

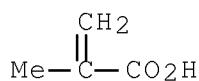
CMF C7 H12 O3

CCI IDS

CM 4

CRN 79-41-4

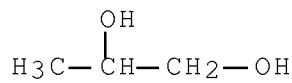
CMF C4 H6 O2



CM 5

CRN 57-55-6

CMF C3 H8 O2



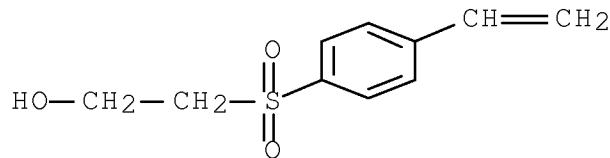
RN 700871-52-9 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with butyl 2-propenoate, 2-[(4-ethenylphenyl)sulfonyl]ethanol and 1,2-propanediol mono(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 700870-27-5

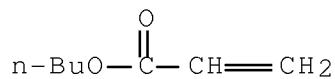
CMF C10 H12 O3 S



CM 2

CRN 141-32-2

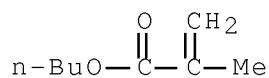
CMF C7 H12 O2



CM 3

CRN 97-88-1

CMF C8 H14 O2

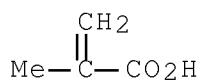


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CRN 27813-02-1  
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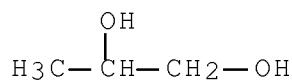
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CRN 79-41-4  
 CMF C4 H6 O2



CM 6

CRN 57-55-6  
 CMF C3 H8 O2



## RETABLE

Referenced Author Referenced	Year	VOL	PG	Referenced Work (RWK)	File
(RAU)	(RPY)	(RVL)	(RPG)		

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Boinon, B | 1989 | 190 | 241 | MAKRMOL CHEM | HCAPLUS
Hoechst Ag | 1952 | | | DE 842198 C | HCAPLUS
Jaeger, D | 1986 | 51 | 3956 | J ORG CHEM | HCAPLUS
Zhu, J | 1999 | 66 | 213 | POLYMER DEGRADATION | HCAPLUS
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=> d 142 3,6,9,12,15,18,21,24,27,30,33,36,39,42,45,48,51,54,57,60, 63, 65  
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L42 ANSWER 3 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN  
 AN 2003:815288 HCAPLUS Full-text  
 DN 139:292669  
 TI Polyurethane resin, composition for optical lenses, and impact  
 strength synthetic resin lenses  
 IN Tamura, Kanichi; Mitsuuchi, Shoichi; Chang, Chung-Tang  
 PA Talex Optical Co., Ltd., Japan; Shuang Bang Industrial Corporation  
 SO Eur. Pat. Appl., 11 pp.  
 CODEN: EPXXDW  
 DT Patent  
 LA English  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1352916	A1	20031015	EP 2003-8202	200304 08
	EP 1352916	B1	20061227		
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	JP 3905409	B2	20070418		
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	CN 1450365	A	20031022	CN 2003-109228	200304

US 20030195323 A1 20031016 US 2003-409852

200304  
10

US 7216976 B2 20070515

PRAI JP 2002-108079 A 20020410

AB An impact resistant lens in which transparency of a synthetic lens material polyurethane and releasability are improved to improve productivity and no stria are produced. The lens is manufactured by casting and curing a composition of a prepolymer obtained by reacting an alicyclic polyisocyanate having  $\geq 2$  isocyanate groups with a polyol having  $\geq 2$  hydroxy groups, an internal mold lubricant, and a decolored aromatic diamine. Thus, a prepolymer of PTMG 1000 200, trimethylolpropane 4, Desmodur W 224 parts Separl 441-100 and Megafac F-470 lubricant 1200 ppm was cast molded with MOCA (ISOCROSS WM) crosslinker, and cured at 100 °C for 20 h to give plastic lens having Abbe number 38 and good impact strength.

IC ICM C08G018-10

ICS C08G018-75

CC 35-5 (Chemistry of Synthetic High Polymers)

Section cross-reference(s): 38

IT 71183-10-3, Separl 441-100 206281-34-7, Megafac F-470

RL: MOA (Modifier or additive use); USES (Uses)

(lubricant; polyurethane-polyurea impact-resistant lenses)

IT 206281-34-7, Megafac F-470

RL: MOA (Modifier or additive use); USES (Uses)

(lubricant; polyurethane-polyurea impact-resistant lenses)

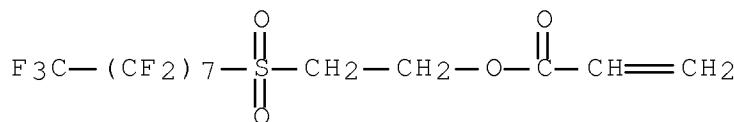
RN 206281-34-7 HCPLUS

CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 124576-86-9

CMF C13 H7 F17 O4 S



Referenced Author Referenced	Year	VOL	PG	Referenced Work	
(RAU)	(RPY)	(RVL)	(RPG)	(RWK)	File
Miyazaki, T	1990			US 4927901 A	HCAPLUS
Slagel, E	2000			US 6127505 A	HCAPLUS
Talex Optical Co Ltd	2002			EP 1197505 A	HCAPLUS

L42 ANSWER 6 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2003:40252 HCAPLUS Full-text

DN 138:115076

TI Transfer printing and its intermediate receptor sheets having adhesive layers with flat surface for uniform transfer

IN Totsuka, Mikio; Shimomura, Akihiro

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI JP 2003015306	A	20030117	JP 2001-203564	20010704

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PRAI JP 2001-203564 20010704

OS MARPAT 138:115076

AB The sheet comprises a support and  $\geq 2$  polymer layers, at least one of which contains surfactants of homopolymers of  $C_nF_{2n+1}LCH_2CH_2OCOCR:CH_2$  [ $n = 2-14$ ; R = H, C1-10-alkyl; L = single bond, divalent group containing atoms selected from O, N, S, and C (e.g.  $CH_2CH_2SO_2NR_1$ , R1 = R)] with  $M_w \geq 2000$ . The printing method contains (A) transferring an image of photoimaging materials to the intermediated receptor sheet and (B) further transferring the image to a permanent receptor.

IC ICM G03F007-105

ICS G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 206281-34-7

RL: TEM (Technical or engineered material use); USES (Uses)  
(Megafac F 470, surfactant; fluoropolymer surfactant for transfer printing intermediate receptor sheets with uniform transfer)

IT 206281-34-7

RL: TEM (Technical or engineered material use); USES (Uses)  
 (Megafac F 470, surfactant; fluoropolymer surfactant for transfer  
 printing intermediate receptor sheets with uniform transfer)

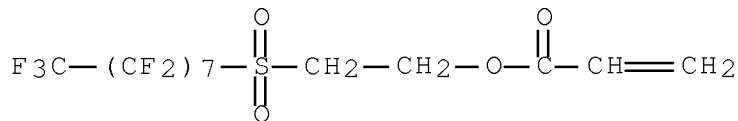
RN 206281-34-7 HCPLUS

CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-  
 heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX  
 NAME)

CM 1

CRN 124576-86-9

CMF C13 H7 F17 O4 S



L42 ANSWER 9 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN

AN 2003:36931 HCPLUS Full-text

DN 138:115045

TI Photosensitive image receiving sheet suitable for making colorproof  
 and transfer image formation method

IN Totsuka, Mikio; Shimomura, Akihiro

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003015284	A	20030115	JP 2001-203562	20010704

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PRAI JP 2001-203562 20010704

OS MARPAT 138:115045

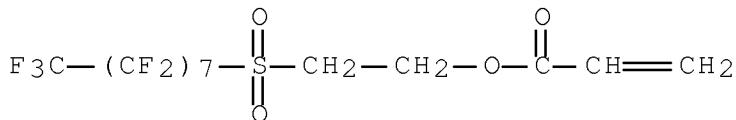
AB A photosensitive image receiving sheet comprises on a support 2 image  
 receiving layers comprising organic polymers, wherein the image  
 receiving layer is a photopolymerizable adhesive layer and the

photosensitive image transfer sheet contains a fluorosurfactant comprising a  $\geq 2000$  weight average mol. weight homopolymer of  $C_nF_{2n+1}-L-CH_2CH_2-O-C(:O)-CR:CH_2$  [ $n = 2-14$ ;  $R = H$ , C1-10-alkyl;  $L$  = single bond, divalent organic group containing O, N, S, and/or C]. The transfer image formation method comprises a process to transfer the image onto a photosensitive image receiving sheet, and a process to transfer the image on the photosensitive image receiving sheet onto a permanent support.

IC ICM G03F007-004  
 ICS G03F003-10  
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 Section cross-reference(s): 42  
 IT 206281-34-7  
 RL: MOA (Modifier or additive use); USES (Uses)  
 (Megafac F 470; specified fluoropolymer surfactant in photosensitive image receiving sheet suitable for making colorproof)  
 IT 206281-34-7  
 RL: MOA (Modifier or additive use); USES (Uses)  
 (Megafac F 470; specified fluoropolymer surfactant in photosensitive image receiving sheet suitable for making colorproof)  
 RN 206281-34-7 HCAPLUS  
 CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 124576-86-9  
 CMF C13 H7 F17 O4 S



L42 ANSWER 12 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN  
 AN 2002:977911 HCAPLUS Full-text  
 DN 138:57578  
 TI Reactive oligomers, compositions, and application of crosslinkable

oligomers onto a substrate

IN Heilmann, Steven M.; Gaddam, Babu N.; Abuelyaman, Ahmed S.; Fansler, Duane D.; Jones, Todd D.; Kavanagh, Maureen A.; Lewandowski, Kevin M.; Wendland, Michael S.

PA 3M Innovative Properties Company, USA

SO PCT Int. Appl., 53 pp.

CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2002102909	A1	20021227	WO 2002-US10447	200204 03

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W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH,  
CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD,  
GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ,  
LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ,  
NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ,  
TM, TN, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZM, ZW  
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE,  
CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT,  
SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,  
SN, TD, TG

US 20030096908	A1	20030522	US 2001-884173	200106 19
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US 6635690	B2	20031021		
AU 2002303222	A1	20030102	AU 2002-303222	200204 03

&lt;--

EP 1401976	A1	20040331	EP 2002-731236	200204 03
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EP 1401976	B1	20051102		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
JP 2004532926	T	20041028	JP 2003-506371	200204 03

&lt;--

AT 308597	T	20051115	AT 2002-731236	
				200204
				03
			<--	
US 20030212210	A1	20031113	US 2003-455571	
				200306
				04
US 7015286	B2	20060321		
US 20030216519	A1	20031120	US 2003-454880	
				200306
				04

US 7074858 B2 20060711

PRAI US 2001-884173 A 20010619  
WO 2002-US10447 W 20020403

AB The coating compns. are prepared from a first oligomer containing reactive functional groups capable of reaction at effective rates (at normal processing temps.) with a co-reactive second component possessing functionality that is complementary to that of the first oligomer. The compns. may be used as coatings, including hard surface coatings, clear coatings, powder coatings and pattern coatings, adhesives, including pressure sensitive adhesives and not melt adhesives, sealants, optical coatings, blown microfibers (BMF), high refractive index optical materials, barrier films, in microreplication, low adhesion backsizes (LABs), and release coatings.

IC ICM C09D201-08

CC 42-10 (Coatings, Inks, and Related Products)

Section cross-reference(s): 35

IT 479401-18-8P 479401-21-3P 479401-22-4P 479401-23-5P

479401-25-7P 479401-26-8P 479401-29-1P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (melt-processable crosslinkable oligomers as adhesives and coatings)

IT 479401-25-7P 479401-26-8P

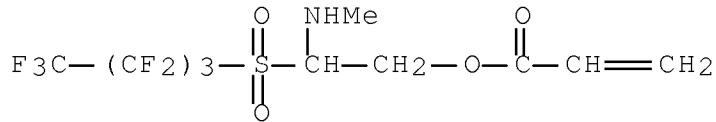
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (melt-processable crosslinkable oligomers as adhesives and coatings)

RN 479401-25-7 HCPLUS

CN 2-Propenoic acid, 2-(dimethylamino)ethyl ester, polymer with 2-ethenyl-4,4-dimethyl-5(4H)-oxazolone and 2-(methylamino)-2-[(nonafluorobutyl)sulfonyl]ethyl 2-propenoate (9CI) (CA INDEX NAME)

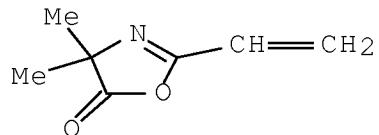
10/535,333

CRN 479401-24-6  
CMF C10 H10 F9 N O4 S



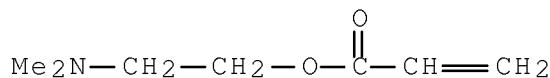
CM 2

CRN 29513-26-6  
CMF C7 H9 N O2



CM 3

CRN 2439-35-2  
CMF C7 H13 N O2

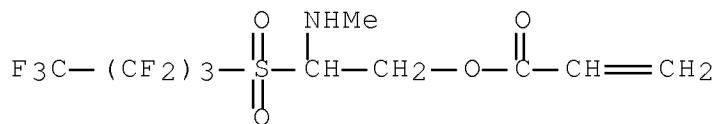


RN 479401-26-8 HCAPLUS  
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with  
2-(dimethylamino)ethyl 2-propenoate and  
2-(methylamino)-2-[ (nonafluorobutyl)sulfonyl]ethyl 2-propenoate  
(9CI) (CA INDEX NAME)

CM 1

CRN 479401-24-6

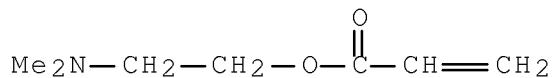
CMF C10 H10 F9 N 04 S



CM 2

CRN 2439-35-2

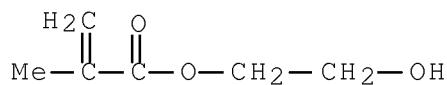
CMF C7 H13 N 02



CM 3

CRN 868-77-9

CMF C6 H10 O3



## RETABLE

Referenced Author Referenced	Year	VOL	PG	Referenced Work	File
(RAU)	(RPY)	(RVL)	(RPG)	(RWK)	
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BASF Corp	1996		EP 0718332 A	HCAPLUS
Burtscher, P	1999		US 5886064 A	HCAPLUS
Heilmann, S	1992		US 5081197 A	HCAPLUS
Heilmann, S	1992		US 5091489 A	HCAPLUS
Rasmussen, J	1988		US 4777276 A	HCAPLUS

L42 ANSWER 15 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2002:726803 HCAPLUS Full-text

DN 137:264012

TI Gas-barrier laminated sheets with improved adhesion

IN Kubo, Hideki; Shibahara, Sumio; Matsuda, Yutaka

PA Sumitomo Bakelite Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

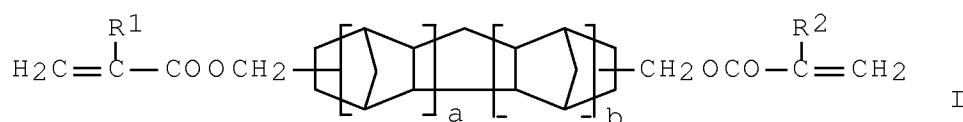
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002273836	A	20020925	JP 2001-79073	20010319

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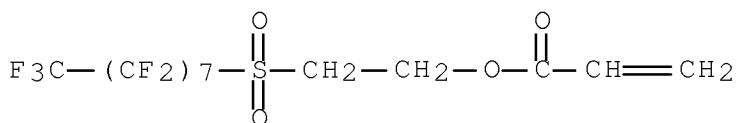
PRAI JP 2001-79073 20010319

GI



AB The sheets comprise substrate sheets containing crosslinked polymers prepared from alicyclic di(meth)acrylate monomers I (R1, R2 = H, Me; a = 1-2; b = 0-1), undercoating layers containing polymers and surfactants, and inorg. layers. Thus, a UV-cured dicyclopentadienyl dimethacrylate polymer substrate sheet was coated with a composition containing Celloxide 2021P (alicyclic epoxy resin) 100, bisphenol S 3, and F 177 (F-containing surfactant) 1 part, heat-cured, and coated with a silicon oxide layer by sputtering to give a laminated sheet with good heat and water resistance.

IC ICM B32B027-30  
 ICS C08F002-44; C08F002-46; C08F020-20  
 CC 38-3 (Plastics Fabrication and Uses)  
 IT 85568-56-5, F 177 206281-34-7, Megafac F 470  
 299190-83-3, Megafac F 472  
 RL: MOA (Modifier or additive use); TEM (Technical or engineered  
 material use); USES (Uses)  
 (undercoating layer; gas-barrier laminated sheets with improved  
 adhesion)  
 IT 206281-34-7, Megafac F 470  
 RL: MOA (Modifier or additive use); TEM (Technical or engineered  
 material use); USES (Uses)  
 (undercoating layer; gas-barrier laminated sheets with improved  
 adhesion)  
 RN 206281-34-7 HCAPLUS  
 CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-  
 heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX  
 NAME)  
 CM 1  
 CRN 124576-86-9  
 CMF C13 H7 F17 O4 S



L42 ANSWER 18 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN  
 AN 2002:314540 HCAPLUS Full-text  
 DN 136:332887  
 TI Manufacture of optical anisotropic material  
 IN Tanaka, Koichi; Emori, Hiroyuki; Yoshioka, Kenichiro  
 PA Nippon Kayaku Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 5 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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 PI JP 2002122737 A 20020426 JP 2000-316182  
 200010  
 17

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PRAI JP 2000-316182 20001017

AB The material is manufactured by the steps of (1) coating a liquid crystal solution containing a fluorosurfactant 0.5-3 weight parts (per 100 weight parts liquid crystal composition) on an alignment-treated substrate and (2) removing the solvent and aligning the liquid crystal. The material without drying unevenness is obtained.

IC ICM G02B005-30

ICS G02F001-1336

CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 73

IT 11114-17-3, Fluorad FC 430 146701-74-8, Eftop EF 802

206281-34-7, Megafac F 470

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(optical anisotropic material manufactured by coating liquid crystal

solution containing fluorosurfactant)

IT 206281-34-7, Megafac F 470

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(optical anisotropic material manufactured by coating liquid crystal

solution containing fluorosurfactant)

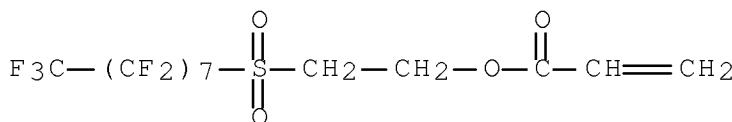
RN 206281-34-7 HCPLUS

CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 124576-86-9

CMF C13 H7 F17 O4 S



L42 ANSWER 21 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN  
 AN 2001:270429 HCAPLUS Full-text  
 DN 134:312068  
 TI Radiation-curable resin compositions for small three-dimensional moldings  
 IN Takano, Kiyoshi; Kinoshita, Hiroshi; Hashimoto, Yutaka  
 PA Dainippon Ink and Chemicals, Inc., Japan  
 SO Jpn. Kokai Tokkyo Koho, 22 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001106710	A	20010417	JP 1999-286691	199910 07

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PRAI JP 3937663 B2 20070627  
 PRAI JP 1999-286691 19991007  
 AB The compns. useful for manufacture of optical lenses and microlens arrays contain surfactants bearing fluoroalkyl groups and polar groups (e.g., polyoxyalkylene or OH groups). Thus, a surfactant was prepared by radical polymerization of H2C:CHCO2CH2CH2C8F17 (I) 16, M 230G (a polyoxyethylene group-containing methacrylate) 71, Me methacrylate 8, and 2-hydroxyethyl methacrylate 5 parts. A composition containing H2C:CHCO2CH2CH2C12F25 23.6, dicyclopentenyl acrylate (II) 2.8, neopentyl glycol diacrylate 15.0, the surfactant 1.0, I-dicyclopentanyl acrylate-isobornyl acrylate-II copolymer 58.1, and a photoinitiator 0.5 part was irradiated by UV in a mold to give a lens showing light transmittance 93% at 460 nm, n 1.446, and good mold release property.  
 IC ICM C08F002-44  
 ICS C08F002-44; C08F002-00; C08F002-46; C08L033-00; C08L071-02;  
 G02B001-04; G02B003-00  
 CC 38-3 (Plastics Fabrication and Uses)  
 Section cross-reference(s): 73  
 IT 52550-45-5P 206281-34-7P, Megafac F 470 287395-86-2P  
 303740-78-5P, Megafac F 177S 334985-74-9P  
 RL: IMF (Industrial manufacture); MOA (Modifier or additive use);  
 PREP (Preparation); USES (Uses)  
 (surfactants; radiation-curable resin compns. for optical lenses)  
 IT 206281-34-7P, Megafac F 470  
 RL: IMF (Industrial manufacture); MOA (Modifier or additive use);

PREP (Preparation); USES (Uses)

(surfactants; radiation-curable resin compns. for optical lenses)

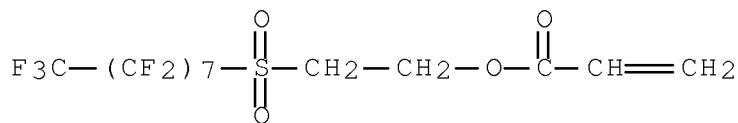
RN 206281-34-7 HCPLUS

CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 124576-86-9

CMF C13 H7 F17 O4 S



L42 ANSWER 24 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN

AN 1999:802694 HCPLUS Full-text

DN 132:42876

TI Negative-working lithographic printing original plate and formation of lithographic printing plate

IN Shimizu, Shinji; Watanabe, Hiroshi; Kojima, Yasuhiko; Koe, Koji; Tashiro, Namiyuki

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI JP 11348446	A	19991221	JP 1998-165050	199806
				12

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PRAI JP 1998-165050 19980612

AB The plate has a heat-sensitive layer containing a photothermal conversion substance, anionic self-dispersing resin particles with acid value 10-300 and average particle size 0.005-15  $\mu\text{m}$ , and a F- containing surfactant on a support having a hydrophilic surface. The

method involves (1) image-exposing using high-d. energy, (2) forming a printing plate image by selectively removing the layer, and (3) washing by H<sub>2</sub>O, gum-treating, and drying. The plate is useful for direct image-printing using high-energy beam.

IC ICM B41N001-14

ICS G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 85568-56-5, Megafac F 177 206281-34-7, Megafac F 470

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(manufacture of neg.-working lithog. printing plate containing F-containing

surfactant, photothermal conversion substance, and resin particles)

IT 206281-34-7, Megafac F 470

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(manufacture of neg.-working lithog. printing plate containing F-containing

surfactant, photothermal conversion substance, and resin particles)

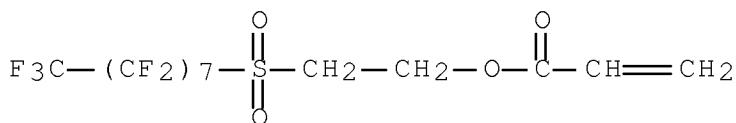
RN 206281-34-7 HCPLUS

CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 124576-86-9

CMF C13 H7 F17 O4 S



L42 ANSWER 27 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN

AN 1999:298575 HCPLUS Full-text

DN 130:359322

TI Original plates for lithographic printing and manufacture of the

printing plates  
 IN Shimizu, Shinji; Kojima, Yasuhiko  
 PA Dainippon Ink and Chemicals, Inc., Japan  
 SO Jpn. Kokai Tokkyo Koho, 13 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11125897	A	19990511	JP 1997-288445	199710 21

&lt;--

PRAI JP 1997-288445 19971021  
 AB The original plate comprises a support, a pos. photosensitive layer, and a resin mask layer mainly containing substances which generate heat by absorption of light, resin particles of average size 0.005-15  $\mu$ m, and F-containing surfactants. The printing plates are manufactured by image formation by irradiation of high d. energy beam followed by wet removal of the unirradiated part. The printing plates are also manufactured by (1) image formation by irradiation of high d. energy beam, (2) wet removal of the unirradiated part for mask image formation, (3) formation of latent image on pos. layer by exposure of the layer with active light beam, (4) removal of the mask, (5) pos. development of the layer, and (6) rinsing, gum treatment, and drying. The plates are suitable as computer to plates.  
 IC ICM G03F007-00  
 ICS B41C001-10; B41N001-14; G03F001-00; G03F007-004  
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 Section cross-reference(s): 38, 39  
 IT 79-10-7D, Acrylic acid, polymers with carbon black, graft 85568-56-5, Megafac F 177 206281-34-7, Megafac F 470 224966-09-0, CWA  
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)  
 (resin mask layers containing light-absorbing heat-generating compound,  
 resin particle, and F-containing surfactant for lithog. printing plate for computer to plate process)  
 IT 206281-34-7, Megafac F 470  
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)  
 (resin mask layers containing light-absorbing heat-generating

compound,

resin particle, and F-containing surfactant for lithog. printing plate for computer to plate process)

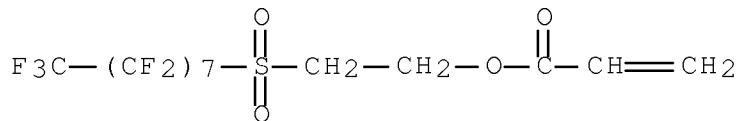
RN 206281-34-7 HCPLUS

CN 2-Propenoic acid, 2-[(1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoroctyl)sulfonyl]ethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 124576-86-9

CMF C13 H7 F17 O4 S



L42 ANSWER 30 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN

AN 1997:107197 HCPLUS Full-text

DN 126:124741

OREF 126:23979a,23982a

TI Preparation of printing plates by electrophotography with high image qualities in the plates and prints

IN Kato, Eiichi; Nakazawa, Jusuke

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 89 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08292611	A	19961105	JP 1996-36726	199602 23
US	5648191	A	19970715	US 1996-605440	199602 22

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PRAI JP 1995-60079 A 19950224

AB The title plates are prepared by placing a peelable first transfer layer of mainly resins that can be removed by chemical reaction; forming an electrophotog. toner image on the above layer; transferring the toner image to first receptor [by (i) forming peelable second transfer layer containing mainly the above resins then transferring the toner image together with the transfer layer to the first receptor; or (ii) transferring the toner image together with the first transfer layer on to the receptor having peelable second transfer layer of mainly the above resins]; transferring the toner image together with the first transfer layer to final receptor becoming lithog.-printable hydrophilic surface during printing; then removing second transfer layer and first transfer layer in the non-image part from the receptor by chemical treatment.

IC ICM G03G013-26  
ICS G03G007-00

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 65697-22-5P, Acrylic acid-benzyl methacrylate copolymer  
150624-67-2P 150624-77-4P 150624-89-8P 150625-22-2P  
155292-83-4P 155292-84-5P 155292-85-6P 155292-86-7P  
155292-87-8P 155292-88-9P 155292-90-3P 155292-96-9P  
157966-19-3P 166594-77-0P, Acrylic acid-benzyl methacrylate-2-methoxyethyl methacrylate copolymer 169045-58-3P  
169045-60-7P, Acrylic acid-benzyl methacrylate-2-butoxyethyl methacrylate copolymer 169045-63-0P, Acrylic acid-methyl methacrylate-2-propoxyethyl methacrylate copolymer 169045-71-0P  
169045-72-1P 169045-73-2P 169045-75-4P 169045-77-6P  
169045-78-7P 169045-81-2P 169045-82-3P 169045-83-4P  
169045-84-5P 169045-87-8P 169045-93-6P 169045-95-8P  
169045-97-0P 169045-98-1P 169046-25-7P 169046-26-8P  
169046-28-0P 169046-29-1P 169046-30-4P 169046-32-6P  
169218-33-1P 176762-50-8P, Crotonic acid-vinyl acetate-vinyl valerate copolymer 176762-52-0P, 2,3-Dipropoxycarbonylpropyl methacrylate-methyl methacrylate-2-sulfoethyl methacrylate copolymer  
176762-54-2P 176762-62-2P 176762-63-3P 176762-65-5P  
176762-66-6P 176771-17-8P 176771-19-0P 176771-21-4P  
176771-22-5P 176771-23-6P 183317-12-6P 183317-16-0P, Acrylic acid-dimethylsilanediol-methyl methacrylate-2-pentyloxyethyl methacrylate graft copolymer 183317-19-3P 183317-21-7P  
183317-24-0P 183317-25-1P 183317-26-2P 183317-27-3P  
183317-28-4P 183317-29-5P 183317-31-9P 183317-32-0P  
183317-33-1P 183317-36-4P 183317-61-5P 183317-62-6P  
183317-63-7P 183317-74-0P 183371-63-3P 186094-45-1P  
186094-46-2P 186094-47-3P 186094-48-4P 186094-59-7P  
186094-60-0P 186094-61-1P 186094-62-2P 186094-63-3P  
RL: IMF (Industrial manufacture); TEM (Technical or engineered)

material use); PREP (Preparation); USES (Uses)  
(preparation of printing plates by electrophotog. with high image qualities in the plates and prints)

IT 169045-73-2P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(preparation of printing plates by electrophotog. with high image qualities in the plates and prints)

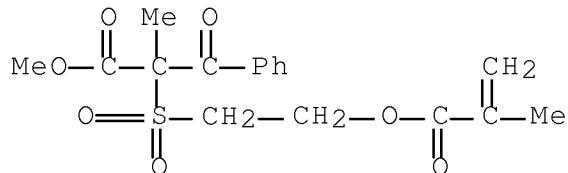
RN 169045-73-2 HCAPLUS

CN Benzene propanoic acid,  $\alpha$ -methyl- $\alpha$ -[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]- $\beta$ -oxo-, methyl ester, polymer with ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 166594-26-9

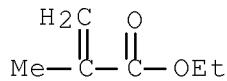
CME C17 H20 07 S



CM 2

CRN 97-63-2

CMF C6 H10 O2



L42 ANSWER 33 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1996:659173 HCAPLUS Full-text

DN 125:288810

OREF 125:53779a, 53782a

TI Manufacture of lithographic printing plate by electrophotographic process

IN Kato, Eiichi

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 79 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08194341	A	19960730	JP 1995-19897	19950113

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PRAI JP 1995-19897 19950113

AB The process comprises forming a toner image on a peelable electrophotog. photoreceptor by using an electrophotog. process, electrodepositing a layer made up of  $\geq 2$  types of resin particles with different Tg (glass transition temperature) on the toner image to form a 1st transfer layer, applying a layer made up of resin particles with a higher Tg to form a 2nd transfer layer, transferring the toner image and the 1st and 2nd transfer layers to a receptor, and removing the 1st and 2nd transfer layers in the non-image section by a chemical process. The resin particles may contain F and/or Si, and are dispersed in a non-aqueous solvent.

IC ICM G03G013-26

ICS G03G013-16

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 26936-24-3, Methyl acrylate-methyl methacrylate-methacrylic acid copolymer 73248-83-6, 2,2,3,4,4,4-Hexafluorobutyl methacrylate-methyl methacrylate copolymer 130030-47-6, Acrylic acid-benzyl methacrylate-ethyl acrylate copolymer 150624-89-8 157966-19-3 161552-54-1 169046-28-0 169046-29-1 169046-30-4 169046-32-6 182558-60-7 182558-61-8, Acrylic acid-2-carboxyethyl acrylate-methyl acrylate-methyl methacrylate copolymer 182558-63-0 182558-65-2, Acrylic acid-2-butoxyethyl acrylate-ethyl methacrylate-methyl methacrylate-2-hydroxyethyl acrylate copolymer 182558-67-4 182558-68-5 182558-69-6 182558-71-0 182558-73-2 182558-75-4 182558-76-5 182558-78-7 182558-80-1 182558-81-2D, thioethoxycarbonylethyl methacrylate terminated 182558-82-3D, thioethylmethacrylate terminated 182558-83-4D, 3-cyanobutanoyloxyethyl acrylate terminated 182558-85-6, Acrylic acid-2-ethoxyethyl acrylate-methyl acrylate copolymer 182558-86-7 182558-87-8 182558-88-9 182558-89-0 182558-90-3 182558-91-4

182558-92-5 182558-93-6 182558-94-7 182558-95-8 182558-97-0

182558-99-2 182559-02-0 182559-04-2 182559-12-2 182559-14-4

RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(manufacture of lithog. printing plate by electrophotog. process)

IT 182558-71-0

RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(manufacture of lithog. printing plate by electrophotog. process)

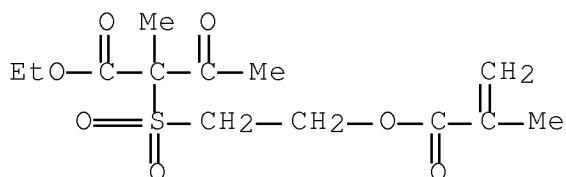
RN 182558-71-0 HCPLUS

CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, ethyl ester, polymer with ethenyl acetate, 2-hydroxyethyl 2-methyl-2-propenoate, 2-[[octahydro-1,3-dioxo-2H-isoindol-2-yl)oxy]sulfonyl]ethyl 2-methyl-2-propenoate and phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 182558-70-9

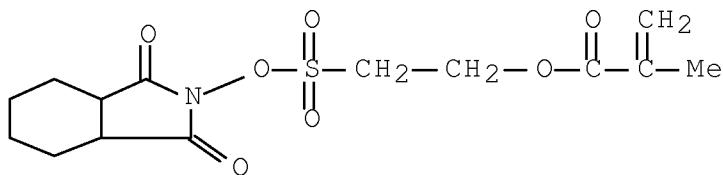
CMF C13 H20 O7 S



CM 2

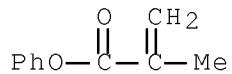
CRN 159319-89-8

CMF C14 H19 N O7 S



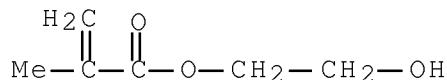
CM 3

CRN 2177-70-0  
CMF C10 H10 O2



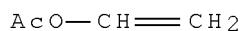
CM 4

CRN 868-77-9  
CMF C6 H10 O3



CM 5

CRN 108-05-4  
CMF C4 H6 O2



L42 ANSWER 36 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN  
AN 1995:995982 HCPLUS Full-text

DN 124:101890

OREF 124:18773a,18776a

TI Apparatus and method for preparation of printing plate by  
electrophotographic process

IN Kato, Eiichi  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 147 pp.  
 CODEN: EPXXDW

DT Patent  
 LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 679957	A1	19951102	EP 1995-106212	199504 25
				<--	
	EP 679957	B1	20000315		
	R: DE, GB				
	US 5561014	A	19961001	US 1995-426740	199504 21
				<--	
	JP 08015925	A	19960119	JP 1995-125592	199504 27
				<--	

PRAI JP 1994-110198 A 19940427

AB A method for preparation of a printing plate by an electrophotog. process comprises forming a toner image on an electrophotog. light-sensitive element by an electrophotog. process, providing a peelable transfer layer mainly containing a resin capable of being removed upon a chemical reaction treatment on the toner image, transferring the toner image together with the transfer layer from the light-sensitive element to a receiving material having a surface capable of providing a hydrophilic surface suitable for lithog. printing at the time of printing, and removing the transfer layer in the non-image area by the chemical reaction treatment. According to the method, good duplicated images are formed without taking the electrophotog. characteristics of transfer layer used into consideration. The transfer layer is excellent in transferability and can be achieved. A conventional electrophotog. light-sensitive element can be utilized by applying a compound for imparting the desired releasability to the surface thereof. An apparatus suitable for use in the method is also disclosed.

IC ICM G03G013-28

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 25189-12-2P 172835-50-6P 172835-51-7P 172835-52-8P  
 172835-53-9P 172835-54-0P 172835-55-1P 172835-56-2P

172835-57-3P 172835-59-5P 172835-60-8P 172835-61-9P

172835-62-0P 172835-63-1P 172835-65-3P

RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(core-shell structure thermoplastic resin grain for transfer layer comprising)

IT	172835-15-3P	172835-17-5P	172835-18-6P	172835-19-7P
	172835-20-0P	172835-21-1P	172835-22-2P	172835-23-3P
	172835-24-4P	172835-25-5P	172835-27-7P	172835-29-9P
	172835-31-3P	172835-32-4P	172835-33-5P	172835-34-6P
	172835-35-7P	172835-36-8P	172835-37-9P	172835-38-0P
	172835-39-1P	172835-40-4P	172835-42-6P	172835-43-7P
	172835-44-8P	172835-45-9P	172835-46-0P	172835-47-1P
	172835-49-3P			

RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(thermoplastic resin grain for transfer layer comprising)

IT 172835-59-5P  
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)  
(core-shell structure thermoplastic resin grain for transfer layer comprising)

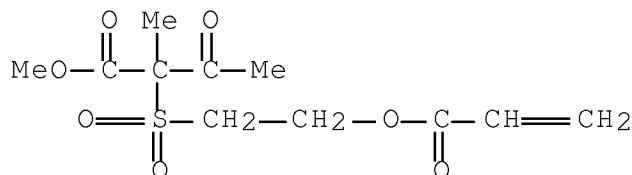
BN 172835-59-5 HCAPLUS

CN Butanedioic acid, bis[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]ester, polymer with 3-[dimethyl(2,2,3,3,3-pentafluoropropyl)silyl]propyl 2-methyl-2-propenoate, hexadecyl 2-methyl-2-propenoate, 2-[(1-(methoxycarbonyl)-1-methyl-2-oxopropyl)sulfonyl]ethyl 2-propenoate and 3-phenylpropyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

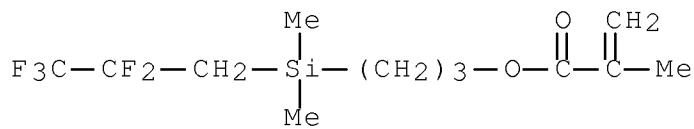
CRN 172835-58-4

CME C11 H16 07 S



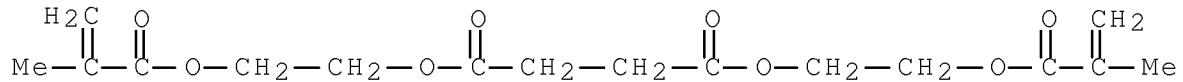
CM 2

CRN 161552-26-7  
 CMF C12 H19 F5 O2 Si



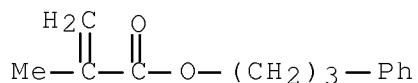
CM 3

CRN 48075-85-0  
 CMF C16 H22 O8



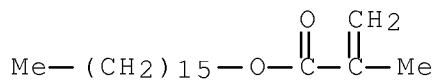
CM 4

CRN 3683-14-5  
 CMF C13 H16 O2



CM 5

CRN 2495-27-4  
 CMF C20 H38 O2



IT 172835-22-2P 172835-44-8P

RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(thermoplastic resin grain for transfer layer comprising)

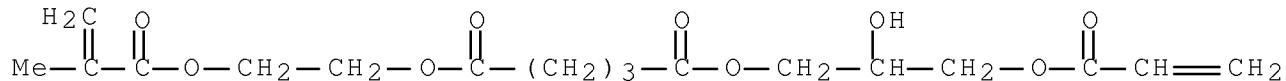
RN 172835-22-2 HCPLUS

CN Pentanedioic acid, 2-hydroxy-3-[(1-oxo-2-propenyl)oxy]propyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with ethyl 2-methyl-2-propenoate, methyl 2-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]ethylsulfonyl]-3-oxobutanoate, methyl 2-propenoate, octadecyl 2-methyl-2-propenoate and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 172835-16-4

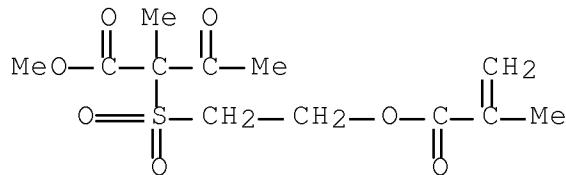
CMF C17 H24 O9



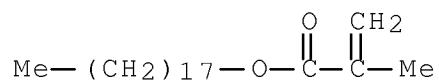
CM 2

CRN 155161-93-6

CMF C12 H18 O7 S



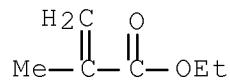
CM 3

CRN 32360-05-7  
CMF C22 H42 O2

CM 4

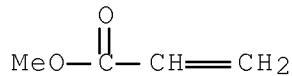
CRN 107-13-1  
CMF C3 H3 N

CM 5

CRN 97-63-2  
CMF C6 H10 O2

CM 6

CRN 96-33-3  
CMF C4 H6 O2



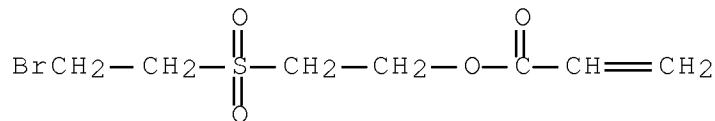
RN 172835-44-8 HCAPLUS

CN Butanedioic acid, bis[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-[(2-bromoethyl)sulfonyl]ethyl 2-propenoate, 2-butoxyethyl 2-methyl-2-propenoate, hexadecyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 118038-14-5

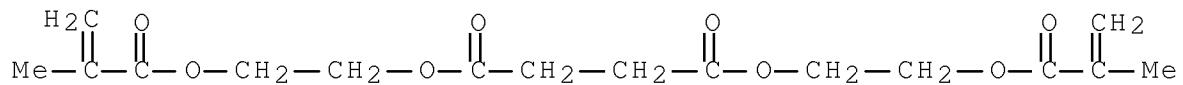
CMF C7 H11 Br O4 S



CM 2

CRN 48075-85-0

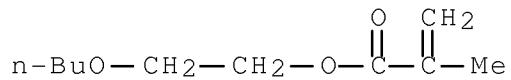
CMF C16 H22 O8



CM 3

CRN 13532-94-0

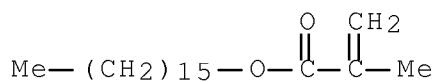
CMF C10 H18 O3



CM 4

CRN 2495-27-4

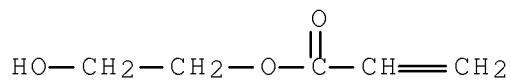
CMF C20 H38 O2



CM 5

CRN 818-61-1

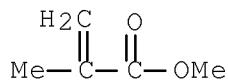
CMF C5 H8 O3



CM 6

CRN 80-62-6

CMF C5 H8 O2



L42 ANSWER 39 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1995:746114 HCAPLUS Full-text

DN 123:156334

OREF 123:27599a,27602a

TI Method for preparation of printing plate by electrophotographic process and apparatus for use therein.

IN Kato, Eiichi; Nakazawa, Yusuke; Osawa, Sadao

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 125 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 632338	A2	19950104	EP 1994-109303	199406 16
				<--	
	EP 632338	A3	19960313		
	EP 632338	B1	19991027		
	R: DE, GB				
	JP 07005727	A	19950110	JP 1993-169846	199306 17
				<--	
	JP 3315207	B2	20020819		
	JP 07064356	A	19950310	JP 1993-232181	199308 26
				<--	
	US 5620822	A	19970415	US 1994-262029	199406 17
				<--	
PRAI	JP 1993-169846	A	19930617		
	JP 1993-232181	A	19930826		

AB A method for preparation of a printing plate by an electrophotog. process comprising forming a peelable transfer layer mainly containing a resin capable of being removed upon a chemical reaction treatment on the surface of an electrophotog. light-sensitive element, forming a toner image on the transfer layer by an electrophotog. process, heat-transferring the toner image together with the transfer layer onto a receiving material a surface of which is capable of providing a hydrophilic surface suitable for lithog. printing at the time of printing, and removing the transfer layer on the receiving material upon the chemical reaction treatment, wherein prior to or simultaneously with the formation of transfer layer a compound which contains a F atom and/or Si atom is applied to the surface of electrophotog. light-sensitive element to improve releasability of the surface of electrophotog. light-sensitive element. The method continuously provides printing plates excellent in image qualities in a stable manner and is suitable for a scanning exposure system using a laser beam. An apparatus suitable for performing the present method is also described.

IC ICM G03G013-28  
ICS G03G005-147

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 158312-76-6P 166594-20-3P 166594-21-4P 166594-23-6P  
166594-24-7P 166594-25-8P 166594-27-0P 166594-29-2P  
166594-31-6P 166594-32-7P 166594-34-9P 166594-36-1P  
166594-37-2P 166594-38-3P 166594-39-4P 166594-41-8P  
166594-43-0P 166594-44-1P 166594-47-4P 166594-48-5P  
166594-49-6P 166594-50-9P 166594-51-0P 166594-52-1P  
166594-54-3P 166594-55-4P 166594-56-5P 166594-58-7P  
166594-60-1P 166594-61-2P 166594-62-3P 166594-63-4P  
166594-66-7P 166594-67-8P 166594-68-9P 166594-69-0P  
166656-23-1P 176762-58-6P

RL: DEV (Device component use); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)  
(release layer; preparation of printing plate by electrophotog. process)

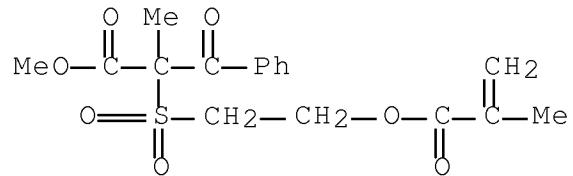
IT 166594-27-0P

RL: DEV (Device component use); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)  
(release layer; preparation of printing plate by electrophotog. process)

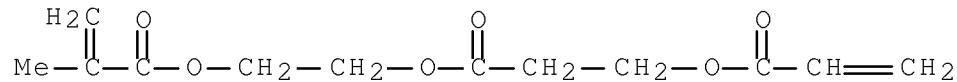
RN 166594-27-0 HCPLUS

CN Benzenepropanoic acid,  $\alpha$ -methyl- $\alpha$ -[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]- $\beta$ -oxo-, methyl ester, polymer with ethyl 2-methyl-2-propenoate, hexadecyl 2-methyl-2-propenoate and 2-[1-oxo-3-[(1-oxo-2-propenyl)oxy]propoxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

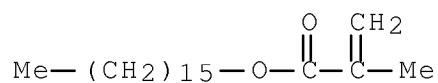
CM 1

CRN 166594-26-9  
CMF C17 H20 O7 S

CM 2

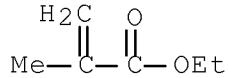
CRN 166594-22-5  
CMF C12 H16 O6

CM 3

CRN 2495-27-4  
CMF C20 H38 O2

CM 4

CRN 97-63-2  
 CMF C6 H10 O2



L42 ANSWER 42 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN

AN 1995:350388 HCPLUS Full-text

DN 122:119020

OREF 122:22067a, 22070a

TI Durable electrophotographic lithographic master

IN Kato, Eiichi; Tashiro, Hiroshi; Ishii, Kazuo

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 71 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06130708	A	19940513	JP 1992-303209	199210 16

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PRAI JP 1992-303209 19921016

AB The title master contains photoconductive layer containing photoconductive compds. and binder resins on an elec. conductive support, and a surface layer, wherein the surface layer contains binders comprising copolymers of (A) components having functional groups forming carboxy group by chemical reaction, (B) components containing functional groups forming SO<sub>3</sub>H, SO<sub>2</sub>H, PO<sub>3</sub>H<sub>2</sub> by the above reaction, and (C) heat and/or photocurable components, and the binders in the photoconductive layer are graft copolymers (Mw 1000-20,000) of monofunctional macromers having polymerizable double bond in the end group of the block B of AB block copolymers of block A containing components containing polar group(s) chosen from PO<sub>3</sub>H<sub>2</sub>, SO<sub>3</sub>H, CO<sub>2</sub>H, phenolic OH, P(O)(OH)R (R = hydrocarbyl, hydrocarbyloxy), and cyclic acid anhydride groups, and block B containing CH(a<sub>1</sub>)C(a<sub>2</sub>)V1R1 units [a<sub>1</sub>, a<sub>2</sub> = H, halogen, cyano, hydrocarbyl; V1 =

CO<sub>2</sub>, O<sub>2</sub>C, (CH<sub>2</sub>)<sub>a</sub>O<sub>2</sub>C, (CH<sub>2</sub>)<sub>a</sub>CO<sub>2</sub>, O, SO<sub>2</sub>, CO, CON(Z1), SONZ1, CONHCO<sub>2</sub>, CONHCONH, C<sub>6</sub>H<sub>4</sub>; Z1 = H, hydrocarbyl; a = 1-3; R1 = H, hydrocarbyl].

IC ICM G03G005-147

ICS G03G005-05; G03G005-06; G03G005-08; G03G005-09; G03G013-28

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 159319-92-3 159319-96-7 159319-99-0 159320-01-1 159320-03-3  
159320-06-6 159320-09-9 159320-10-2 159320-11-3 159320-13-5  
159320-20-4 159320-21-5 159320-22-6 160378-37-0 160378-38-1  
160378-40-5 160378-42-7 160378-49-4

160378 50 7 160378 51 8 160378 52 9 160378 54 1 160631 81 2

160378-50-1 160378-51-8 160378-52-9 160378-54-1 160381-81-2

1608/5-89-8 1608/5-91-2 1608/5-92-3 1608/5-94-5 1608/5-95-6

1608/5-96-7 1608/5-98-9 1608/6-00-6 1608/6-01-7 1608/6-02-8

RL: TEM (Technical or engineered material use); USES (Uses)  
(binders in electrophotog. lithog. masters)

IT 160378-40-5 160378-42-7

RL: TEM (Technical or engineered material use); USES (Uses)

(binders in electrophotog. lithog. masters)

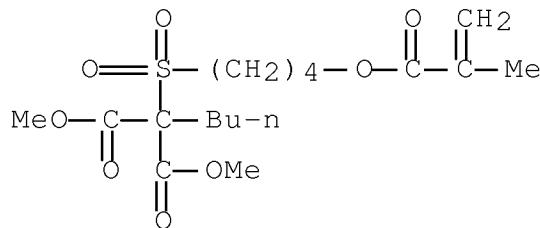
RN 160378-40-5 HCAPLUS

CN Propanedioic acid, butyl[4-[(2-methyl-1-oxo-2-propenyl)oxy]butyl]sulfonyl]-, dimethyl ester, polymer with 1,3-isobenzofurandione, methyl 2-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]-3-oxobutanoate, methyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 160378-39-2

CMF C17 H28 08 S

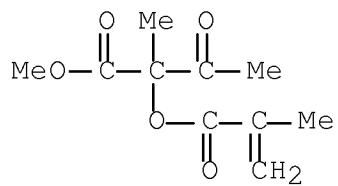


CM 2

CRN 155838-92-9

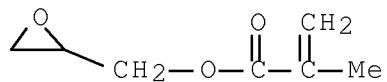
10/535,333

CMF C10 H14 O5



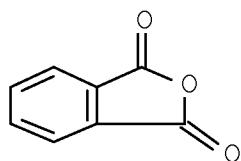
CM 3

CRN 106-91-2  
CMF C7 H10 O3



CM 4

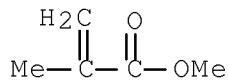
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CMF C8 H4 O3



CM 5

CRN 80-62-6

CMF C5 H8 O2



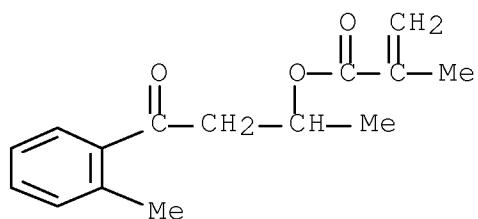
RN 160378-42-7 HCAPLUS

CN Propanedioic acid, methyl[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-, ethyl methyl ester, polymer with 1,3-isobenzofurandione, 1-methyl-3-(2-methylphenyl)-3-oxopropyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

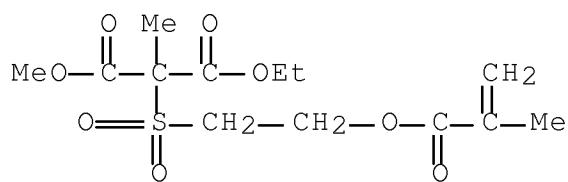
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CMF C15 H18 O3



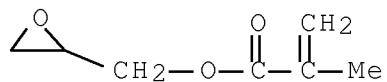
CM 2

CRN 155838-94-1  
CMF C13 H20 08 S



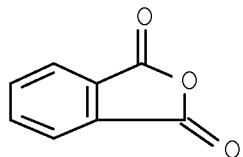
CM 3

CRN 106-91-2  
CMF C7 H10 O3



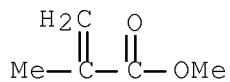
CM 4

CRN 85-44-9  
CMF C8 H4 O3



CM 5

CRN 80-62-6  
CMF C5 H8 O2



L42 ANSWER 45 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1995:304919 HCAPLUS Full-text

DN 122:92881

OREF 122:17363a,17366a

TI Durable electrophotographic lithographic master

IN Kato, Eiichi; Tashiro, Hiroshi; Ishii, Kazuo

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 65 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06130706	A	19940513	JP 1992-301567	199210 15

&lt;--

PRAI JP 1992-301567 19921015

AB The title master contains photoconductive layer containing photoconductive compds. and binder resins on an elec. conductive support, and a surface layer, wherein the surface layer contains binders comprising copolymers of (A) components having functional groups forming carboxy group by chemical reaction, (B) components containing functional groups forming SO<sub>3</sub>H, SO<sub>2</sub>H, PO<sub>3</sub>H<sub>2</sub> by the above reaction, and (C) heat and/or photocurable components, and the binders in the photoconductive layer are star-copolymers (Mw 1000-20,000) containing ≥3 A-B block chains of block A containing CH(a<sub>1</sub>)C(a<sub>2</sub>)CO<sub>2</sub>R<sub>1</sub> units (a<sub>1</sub>, a<sub>2</sub> = H, halogen, cyano; R<sub>1</sub> = hydrocarbyl) and block B containing components containing polar group(s) chosen from PO<sub>3</sub>H<sub>2</sub>, SO<sub>3</sub>H, CO<sub>2</sub>H, P(O)(OH)R<sub>2</sub> (R<sub>2</sub> = hydrocarbyl, hydrocarbyloxy), and cyclic acid anhydride group.

IC ICM G03G005-147

ICS G03G005-05; G03G005-06; G03G005-08; G03G005-09; G03G013-28

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT	159319-90-1	159319-92-3	159319-94-5	159319-96-7	159319-99-0
	159320-03-3	159320-06-6	159320-09-9	159320-10-2	159320-11-3
	159320-13-5	159320-14-6	159320-20-4	159320-21-5	159320-22-6
	160378-37-0	160378-38-1	160378-40-5	160378-47-2	
	160378-48-3	160378-49-4	160378-50-7	160378-51-8	160378-52-9
	160378-54-1	160378-55-2	160378-56-3	160378-59-6	160378-60-9
	160378-62-1	160378-64-3	160378-65-4	160631-81-2	

RL: TEM (Technical or engineered material use); USES (Uses)  
(binders in electrophotog. lithog. masters)

IT 160378-40-5 160378-62-1

RL: TEM (Technical or engineered material use); USES (Uses)  
(binders in electrophotog. lithog. masters)

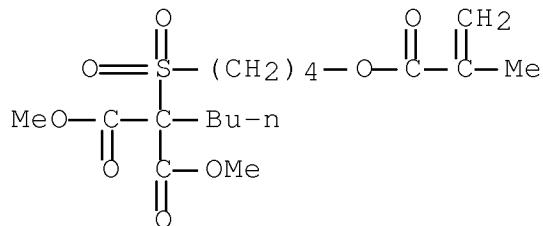
RN 160378-40-5 HCAPLUS

CN Propanedioic acid, butyl[[4-[(2-methyl-1-oxo-2-propenyl)oxy]butyl]sulfonyl]-, dimethyl ester, polymer with 1,3-isobenzofurandione, methyl 2-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]-3-oxobutanoate, methyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI)  
(CA INDEX NAME)

CM 1

CRN 160378-39-2

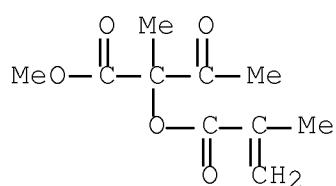
CMF C17 H28 O8 S



CM 2

CRN 155838-92-9

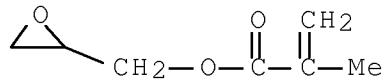
CMF C10 H14 O5



CM 3

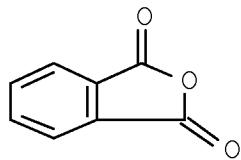
10/535,333

CRN 106-91-2  
CMF C7 H10 O3



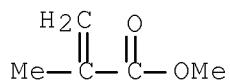
CM 4

CRN 85-44-9  
CMF C8 H4 O3



CM 5

CRN 80-62-6  
CMF C5 H8 O2



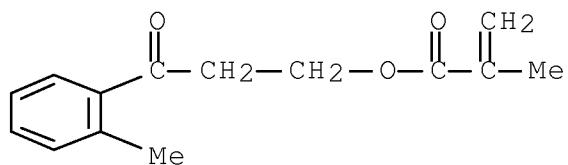
RN 160378-62-1 HCAPLUS  
CN Propanedioic acid, methyl[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-, ethyl methyl ester, polymer with 1,3-isobenzofurandione, methyl 2-methyl-2-propenoate, 3-(2-methylphenyl)-3-oxopropyl 2-methyl-2-propenoate and

oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 160378-61-0

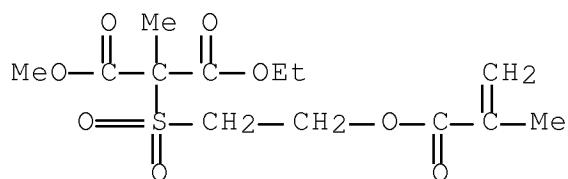
CMF C14 H16 O3



CM 2

CRN 155838-94-1

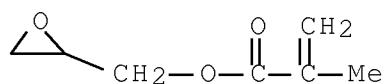
CMF C13 H20 O8 S



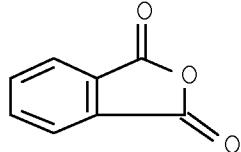
CM 3

CRN 106-91-2

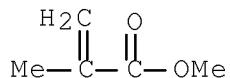
CMF C7 H10 O3



CM 4

CRN 85-44-9  
CMF C8 H4 O3

CM 5

CRN 80-62-6  
CMF C5 H8 O2

L42 ANSWER 48 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN  
 AN 1994:617686 HCAPLUS Full-text  
 DN 121:217686  
 OREF 121:39407a, 39410a  
 TI Electrophotographic lithographic plate master with superior  
     desensitization and good printing performance  
 IN Kato, Eiichi; Tashiro, Hiroshi; Ishii, Kazuo  
 PA Fuji Photo Film Co Ltd, Japan  
 SO Jpn. Kokai Tokkyo Koho, 43 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI JP 05273799 A 19931022 JP 1992-67378 199203  
 25

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PRAI JP 1992-67378 19920325

AB In the title plate master employing a photoreceptor which has on its elec. conductive support  $\geq 1$  photoconductive layer and further a cover layer on the uppermost layer, the cover layer contains  $\geq 1$  binder resin (A) containing (a)  $\geq 1$  polymerizable component capable of giving CO<sub>2</sub>H on chemical reaction, (b)  $\geq 1$  polymerizable component capable of producing SO<sub>3</sub>H, SO<sub>2</sub>H, PO<sub>3</sub>H<sub>2</sub> on the same reaction, and (c)  $\geq 1$  polymerizable component containing thermal and(or) photo curable group.

IC ICM G03G013-28

ICS G03G005-05; G03G005-06; G03G005-08; G03G005-147

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 156623-29-9 156623-31-3 156623-32-4 156623-33-5 156623-34-6  
 156623-35-7 156623-36-8 156623-37-9 156623-38-0  
 156623-39-1 156623-41-5 156623-42-6 156623-43-7 156623-44-8  
 156623-45-9 156623-46-0 156623-47-1 156623-48-2 156623-49-3  
 156623-50-6 156623-51-7 156623-52-8 156623-53-9 156623-54-0

RL: USES (Uses)  
 (as binder, electrophotog. photoreceptor using, for lithog. plate master)

IT 156623-35-7

RL: USES (Uses)  
 (as binder, electrophotog. photoreceptor using, for lithog. plate master)

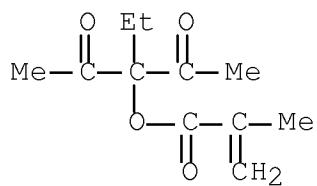
RN 156623-35-7 HCPLUS

CN Propanedioic acid, methyl[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-, ethyl methyl ester, polymer with 1-acetyl-1-ethyl-2-oxopropyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

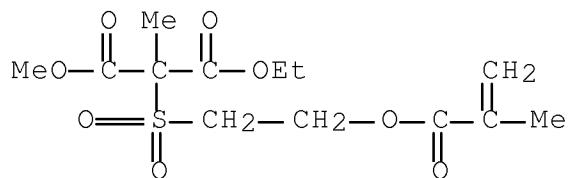
CM 1

CRN 155838-95-2

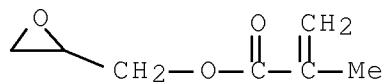
CMF C11 H16 O4



CM 2

CRN 155838-94-1  
CMF C13 H20 O8 S

CM 3

CRN 106-91-2  
CMF C7 H10 O3

L42 ANSWER 51 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN  
 AN 1994:469571 HCPLUS Full-text  
 DN 121:69571  
 OREF 121:12301a,12304a  
 TI Electrophotographic plate for lithographic platemaking  
 IN Kato, Eiichi

PA Fuji Photo Film Co Ltd, Japan  
 SO Jpn. Kokai Tokkyo Koho, 88 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05216293	A	19930827	JP 1992-47654	19920204

&lt;--

PRAI JP 1992-47654 19920204

AB In the title electrophotog. plate for lithog. platemaking possessing  $\geq 1$  photoconductive layers and a claimed surface layer on an electroconductive support, the photoconductive layer contains  $\geq 1$  binder resins (weight average mol. weight  $1 \times 10^3 - 2 \times 10^4$ ) having the repeating unit  $\text{CHa}_1\text{Ca}_2(\text{CO}_2\text{R})$  [ $\text{a}_1, \text{a}_2 = \text{H, halo, CN, hydrocarbyl; R = hydrocarbyl}$ ]  $\geq 30\%$  and  $\geq 1$  polar groups selected from  $\text{PO}_3\text{H}_2$ ,  $\text{SO}_3\text{H}$ ,  $\text{CO}_2\text{H}$ ,  $\text{P}(\text{O})(\text{OH})\text{R}$  ( $\text{R} = \text{hydrocarbyl, oxyhydrocarbyl}$ ), and cyclic acid anhydride group at 1 end of the polymer chain. The claimed surface layer contains dispersed resin particles obtained by polymerizing a monofunctional monomer containing  $\geq 1$  functional groups selected from  $\text{W}_1(\text{CH}_2)^{\text{n}_1}\text{CH}:\text{CH}_2$  and  $\text{W}_2(\text{CH}_2)^{\text{n}_2}\text{CH}_2\text{CH}_2\text{X}$  [ $\text{W}_1, \text{W}_2 = \text{SO}_2, \text{CO, O}_2\text{C}$ ;  $\text{n}_1, \text{n}_2 = 0, 1$ ;  $\text{X} = \text{halo}$ ] with a monofunctional monomer containing substituents containing  $\geq 1$  Si and(or) F atoms in the presence of a soluble dispersion-stabilizing resin. The lithog. plates obtained are capable of withstanding severe use conditions and the electrophotog. plates are amenable to laser scanning exposure.

IC ICM G03G013-28  
 ICS G03G005-05; G03G005-06; G03G005-147  
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 IT 79-41-4D, fluoroalkyl esters, polymers with methacrylates and chloroethylsulfonyl-2-propene 97-90-5D, polymers with methacrylates and chloroethylsulfonyl-2-propene 106-91-2D, polymers with methacrylates and chloroethylsulfonyl-2-propene 142-09-6D, Hexyl methacrylate, polymers with methacrylates and chloroethylsulfonyl-2-propene 149839-06-5D, polymers with methacrylates 151733-27-6 151733-28-7 151733-29-8  
 151733-30-1 151733-31-2 151733-32-3 151733-33-4 151733-34-5  
 151733-35-6 151735-81-8 151752-65-7 151752-80-6  
 151752-81-7 151752-82-8 151752-84-0  
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 151758-74-6 151758-75-7 151758-77-9 151758-82-6

151758-83-7 151758-84-8 151767-53-2 151767-55-4  
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 156349-28-9 156500-17-3

RL: USES (Uses)

(latex particles, electrophotog. lithog. plate using)

IT 151733-35-6 151752-80-6 151752-81-7  
 151752-82-8 151752-84-0 151752-85-1  
 151758-77-9 151758-84-8 151835-58-4

RL: USES (Uses)

(latex particles, electrophotog. lithog. plate using)

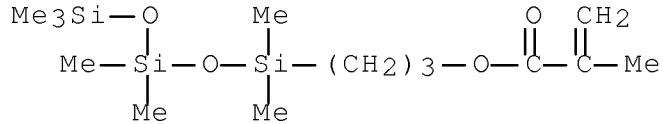
RN 151733-35-6 HCPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester,  
 polymer with 1,2-ethanediyl di-2-propenoate,  
 3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate, methyl  
 2-methyl-2-propenoate and methyl 2-propenoate, graft (9CI) (CA  
 INDEX NAME)

CM 1

CRN 150624-86-5

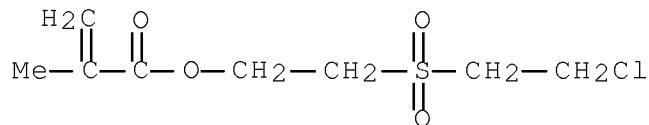
CMF C14 H32 O4 Si3



CM 2

CRN 143131-91-3

CMF C8 H13 Cl O4 S

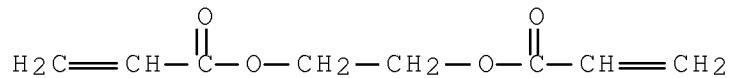


10/535,333

CM 3

CRN 2274-11-5

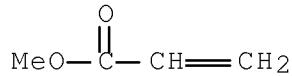
CMF C8 H10 O4



CM 4

CRN 96-33-3

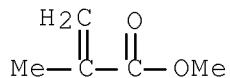
CMF C4 H6 O2



CM 5

CRN 80-62-6

CMF C5 H8 O2

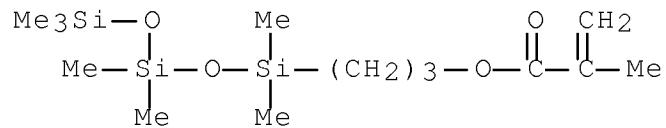


RN 151752-80-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester,  
polymer with 1,2-ethanediyl di-2-propenoate,  
3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate and pentyl  
2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

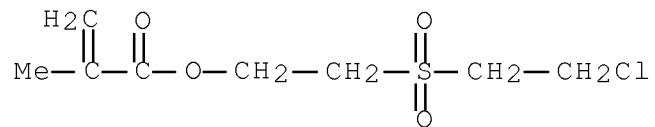
CM 1

CRN 150624-86-5  
CMF C14 H32 O4 Si3



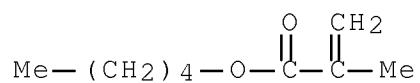
CM 2

CRN 143131-91-3  
CMF C8 H13 C1 O4 S



CM 3

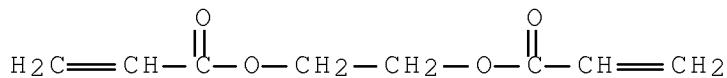
CRN 2849-98-1  
CMF C9 H16 02



CM 4

CRN 2274-11-5

CMF C8 H10 O4



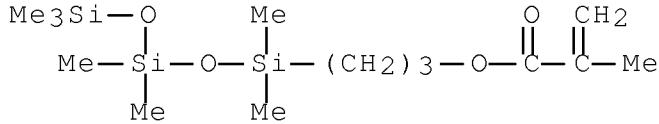
RN 151752-81-7 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with  
 2-[ (2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
 1,2-ethanediyl di-2-propenoate, 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate and 2-propenamide, graft (9CI) (CA INDEX  
 NAME)

CM 1

CRN 150624-86-5

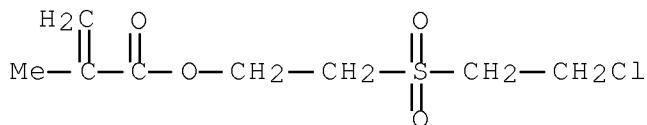
CMF C14 H32 O4 Si3



CM 2

CRN 143131-91-3

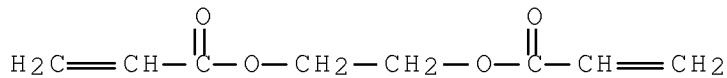
CMF C8 H13 Cl O4 S



10/535,333

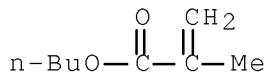
CM 3

CRN 2274-11-5  
CMF C8 H10 O4



CM 4

CRN 97-88-1  
CMF C8 H14 O2



CM 5

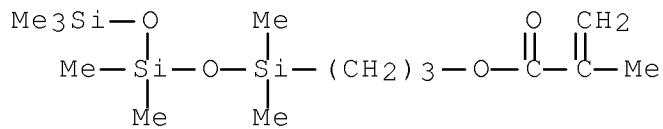
CRN 79-06-1  
CMF C3 H5 N O



RN 151752-82-8 HCAPLUS  
CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with  
2-[(2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
1,2-ethanediyl di-2-propenoate and 3-(heptamethyltrisiloxanyl)propyl  
2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

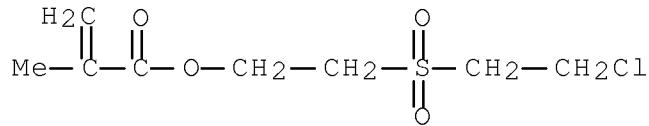
CM 1

CRN 150624-86-5  
 CMF C14 H32 O4 Si3



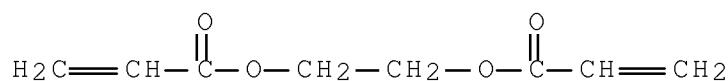
CM 2

CRN 143131-91-3  
 CMF C8 H13 Cl O4 S



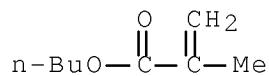
CM 3

CRN 2274-11-5  
 CMF C8 H10 O4



CM 4

CRN 97-88-1  
 CMF C8 H14 O2



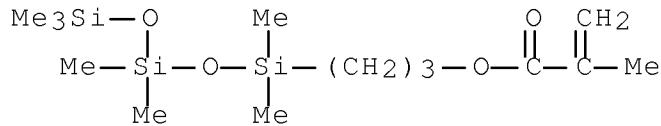
RN 151752-84-0 HCPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester,  
 polymer with 1,2-ethanediyl di-2-propenoate, ethyl  
 2-methyl-2-propenoate and 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 150624-86-5

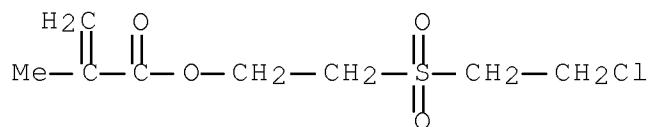
CMF C14 H32 O4 Si3



CM 2

CRN 143131-91-3

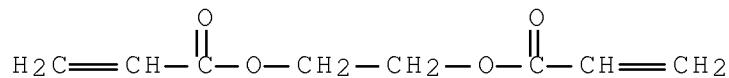
CMF C8 H13 Cl O4 S



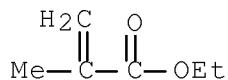
CM 3

CRN 2274-11-5

CMF C8 H10 O4

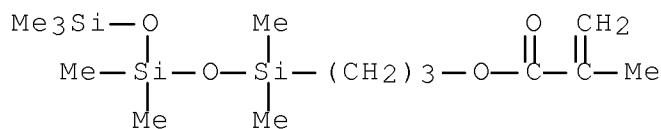


CM 4

CRN 97-63-2  
CMF C6 H10 O2

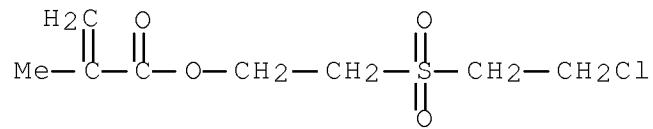
RN 151752-85-1 HCAPLUS  
 CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with  
 2-[ (2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
 1,2-ethanediyl di-2-propenoate, 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate,  
 graft (9CI) (CA INDEX NAME)

CM 1

CRN 150624-86-5  
CMF C14 H32 O4 Si3

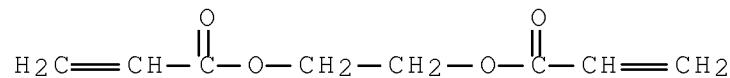
CM 2

CRN 143131-91-3  
 CMF C8 H13 Cl O4 S



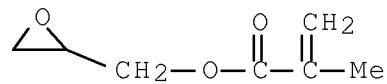
CM 3

CRN 2274-11-5  
 CMF C8 H10 O4



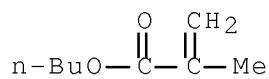
CM 4

CRN 106-91-2  
 CMF C7 H10 O3



CM 5

CRN 97-88-1  
 CMF C8 H14 O2



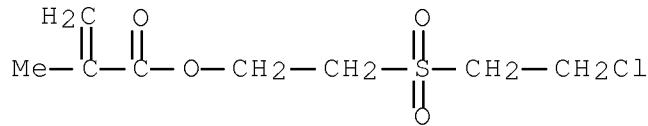
RN 151758-77-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with  
 2-[ (2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
 2,2,3,4,4,4-hexafluorobutyl 2-methyl-2-propenoate, hexyl  
 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate,  
 graft (9CI) (CA INDEX NAME)

CM 1

CRN 143131-91-3

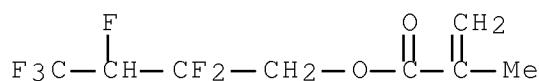
CMF C8 H13 Cl 04 S



CM 2

CRN 36405-47-7

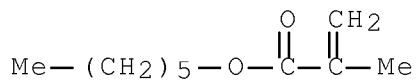
CMF C8 H8 F6 O2



CM 3

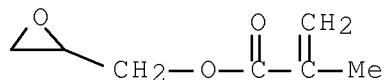
CRN 142-09-6

CMF C10 H18 O2



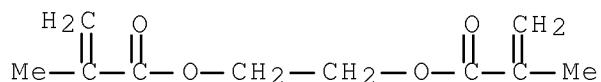
CM 4

CRN 106-91-2  
 CMF C7 H10 O3



CM 5

CRN 97-90-5  
 CMF C10 H14 O4

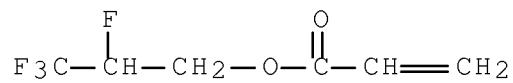


RN 151758-84-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with 3-[ (2-chloroethyl)sulfonyl]propyl 2-methyl-2-propenoate, hexyl 2-methyl-2-propenoate, oxiranylmethyl 2-methyl-2-propenoate and 2,3,3,3-tetrafluoropropyl 2-propenoate, graft (9CI) (CA INDEX NAME)

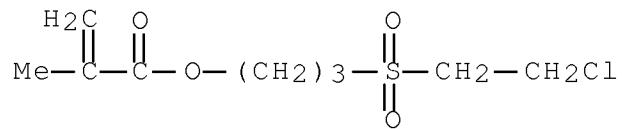
CM 1

CRN 147987-23-3  
 CMF C6 H6 F4 O2



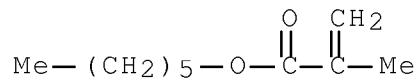
CM 2

CRN 140913-31-1  
 CMF C9 H15 Cl O4 S



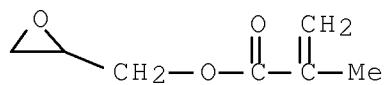
CM 3

CRN 142-09-6  
 CMF C10 H18 O2

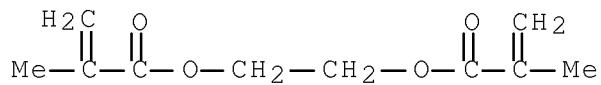


CM 4

CRN 106-91-2  
 CMF C7 H10 O3



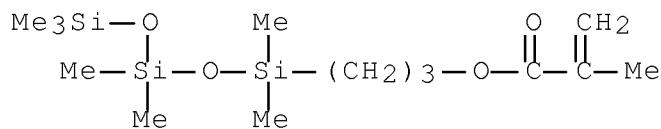
CM 5

CRN 97-90-5  
CMF C10 H14 O4

RN 151835-58-4 HCPLUS

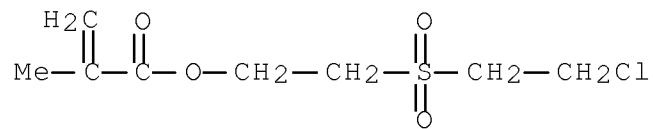
CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester, polymer with dodecyl 2-methyl-2-propenoate polymer with oxiranylmethyl 2-methyl-2-propenoate 2-methyl-2-propenoate, 1,2-ethanediyl di-2-propenoate and 3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 150624-86-5  
CMF C14 H32 O4 Si3

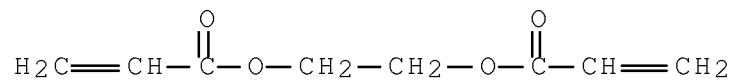
CM 2

CRN 143131-91-3  
CMF C8 H13 Cl O4 S



CM 3

CRN 2274-11-5  
 CMF C8 H10 O4

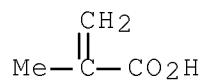


CM 4

CRN 52229-66-0  
 CMF (C16 H30 O2 . C7 H10 O3)x . x C4 H6 O2

CM 5

CRN 79-41-4  
 CMF C4 H6 O2



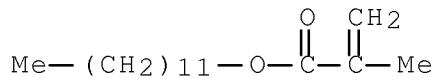
CM 6

CRN 28851-51-6

CMF (C<sub>16</sub> H<sub>30</sub> O<sub>2</sub> . C<sub>7</sub> H<sub>10</sub> O<sub>3</sub>)<sub>x</sub>  
 CCI PMS

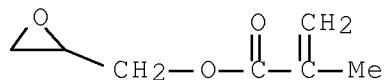
CM 7

CRN 142-90-5  
 CMF C<sub>16</sub> H<sub>30</sub> O<sub>2</sub>



CM 8

CRN 106-91-2  
 CMF C<sub>7</sub> H<sub>10</sub> O<sub>3</sub>



L42 ANSWER 54 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN  
 AN 1994:311462 HCPLUS Full-text  
 DN 120:311462  
 OREF 120:54545a,54548a  
 TI Electrophotographic plates from lithographic plates and lithographic  
 platemaking  
 IN Kato, Eiichi  
 PA Fuji Photo Film Co Ltd, Japan  
 SO Jpn. Kokai Tokkyo Koho, 36 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI JP 05165228 A 19930702 JP 1991-336698 19911219  
 199112  
 19

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PRAI JP 1991-336698 19911219

AB In the title electrophotog. plate used for lithog. printing platemaking and comprised of an electroconductive support provided with  $\geq 1$  photoconductive layers and a surface cover layer, the surface cover layer utilizes  $\geq 1$  resins containing  $\geq 1$  polymer components with the functional group  $\text{SO}_2\text{CXX}_1\text{R}$  [ $\geq 1$  of  $\text{X}, \text{X}_1$  is an electron-withdrawing group; when the sum of the Hammett  $\sigma_P$  values for  $\text{X}, \text{X}_1$  is  $\geq 0.45$ , they may be the same or different from each other;  $\text{R} = \text{H}, \text{CnH}_2\text{n+1}$  ( $\text{n} = 1-6$ )]. Lithog. platemaking is effected by imagewise exposing the title electrophotog. plate, developing to produce a toner image, and desensitizing the toner non-bearing areas with a hydrophilic compound containing a substituent having a Parson's nucleophilic constant of  $\geq 5.5$ . The electrophotog. plate is capable of withstanding long-term storage under severe ambient conditions, possesses superior electrostatic properties, and produces lithog. plates with superior printing characteristics.

IC ICM G03G005-05  
 ICS G03G005-06; G03G005-147; G03G013-28

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 Section cross-reference(s): 35

IT 155161-82-3P 155161-84-5P 155161-86-7P  
 155161-87-8P 155161-88-9P 155161-89-0P  
 155161-90-3P 155161-91-4P 155161-92-5P  
 155161-94-7P 155161-95-8P 155161-96-9P  
 155161-97-0P 155161-98-1P 155161-99-2P  
 155162-00-8P 155162-01-9P 155162-03-1P  
 155162-05-3P 155162-07-5P 155162-09-7P  
 155162-11-1P 155162-14-4P 155162-16-6P  
 155162-19-9P 155162-21-3P 155162-23-5P

RL: PREP (Preparation)  
 (preparation of, as cover layer for electrophotog. plate)

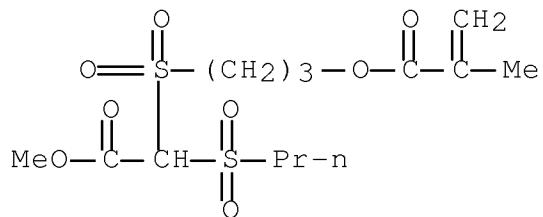
IT 155161-86-7P 155161-87-8P 155161-88-9P  
 155161-89-0P 155161-90-3P 155161-91-4P  
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 155161-99-2P 155162-00-8P 155162-01-9P  
 155162-03-1P 155162-05-3P 155162-11-1P  
 155162-14-4P 155162-19-9P 155162-21-3P

RL: PREP (Preparation)  
 (preparation of, as cover layer for electrophotog. plate)

RN 155161-86-7 HCAPLUS  
 CN 2-Propenoic acid, 2-methyl-,  
 3-[ [2-methoxy-2-oxo-1-(propylsulfonyl)ethyl]sulfonyl]propyl ester,  
 polymer with diethenylbenzene and oxiranylmethyl  
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

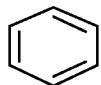
CM 1

CRN 155161-85-6  
 CMF C13 H22 O8 S2



CM 2

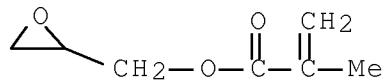
CRN 1321-74-0  
 CMF C10 H10  
 CCI IDS



2 [ D1—CH=CH2 ]

CM 3

CRN 106-91-2  
 CMF C7 H10 O3



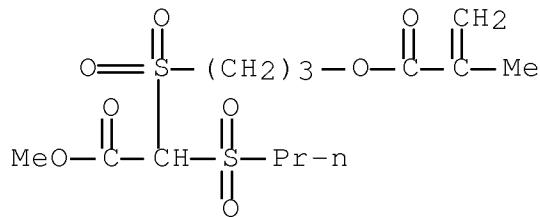
RN 155161-87-8 HCPLUS

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with  
 3-[ [2-methoxy-2-oxo-1-(propylsulfonyl)ethyl]sulfonyl]propyl  
 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI)  
 (CA INDEX NAME)

CM 1

CRN 155161-85-6

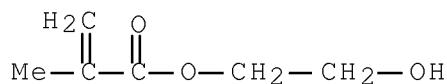
CMF C13 H22 O8 S2



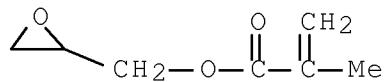
CM 2

CRN 868-77-9

CMF C6 H10 O3

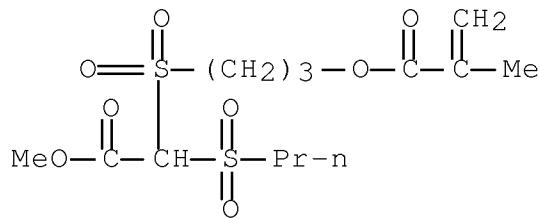


CM 3

CRN 106-91-2  
CMF C7 H10 O3

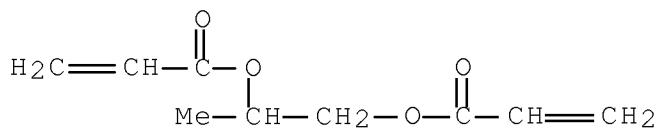
RN 155161-88-9 HCAPLUS  
 CN 2-Propenoic acid, 2-methyl-,  
 3-[2-methoxy-2-oxo-1-(propylsulfonyl)ethylsulfonyl]propyl ester,  
 polymer with 1-methyl-1,2-ethanediyl di-2-propenoate and  
 oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 155161-85-6  
CMF C13 H22 O8 S2

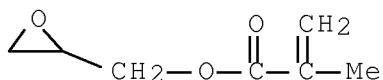
CM 2

CRN 25151-33-1  
CMF C9 H12 O4



CM 3

CRN 106-91-2  
CMF C7 H10 03

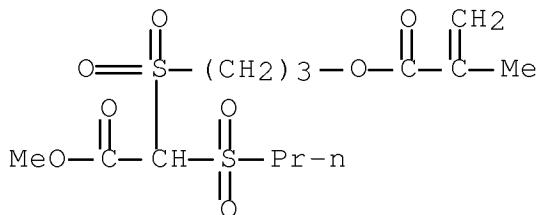


RN 155161-89-0 HCPLUS

CN Hexanedioic acid, diethenyl ester, polymer with  
3-[[2-methoxy-2-oxo-1-(propylsulfonyl)ethyl]sulfonyl]propyl  
2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI)  
(CA INDEX NAME)

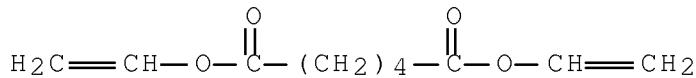
CM 1

CRN 155161-85-6  
CMF C13 H22 08 S2



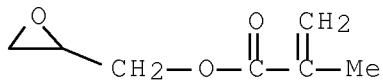
CM 2

CRN 4074-90-2  
 CMF C10 H14 O4



CM 3

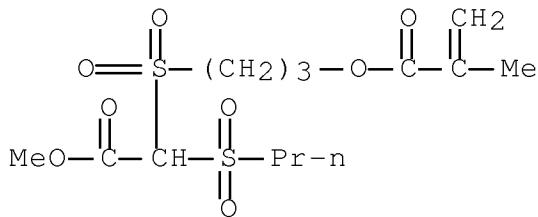
CRN 106-91-2  
 CMF C7 H10 O3



RN 155161-90-3 HCAPLUS  
 CN 2-Propenoic acid, 2-methyl-, ethenyl ester, polymer with  
 3-[ [2-methoxy-2-oxo-1-(propylsulfonyl)ethyl]sulfonyl]propyl  
 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI)  
 (CA INDEX NAME)

CM 1

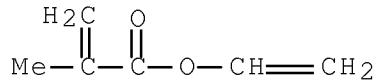
CRN 155161-85-6  
 CMF C13 H22 O8 S2



CM 2

CRN 4245-37-8

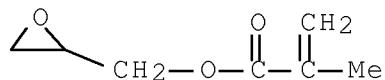
CMF C6 H8 O2



CM 3

CRN 106-91-2

CMF C7 H10 O3



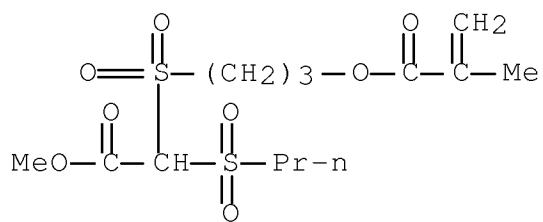
RN 155161-91-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,  
 2-ethyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl  
 ester, polymer with 3-[[2-methoxy-2-oxo-1-  
 (propylsulfonyl)ethyl]sulfonyl]propyl 2-methyl-2-propenoate and  
 oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

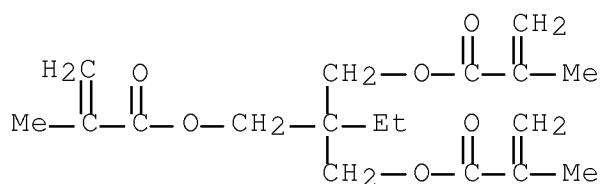
CRN 155161-85-6

CMF C13 H22 O8 S2



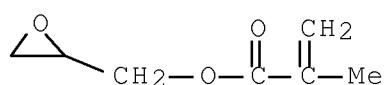
CM 2

CRN 3290-92-4  
CMF C18 H26 O6



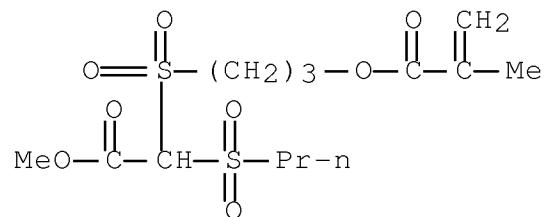
CM 3

CRN 106-91-2  
CMF C7 H10 O3

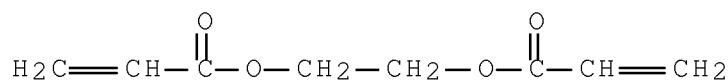


RN 155161-92-5 HCPLUS  
CN 2-Propenoic acid, 2-methyl-,  
3-[[2-methoxy-2-oxo-1-(propylsulfonyl)ethyl]sulfonyl]propyl ester,  
polymer with 1,2-ethanediyl di-2-propenoate and oxiranylmethyl  
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

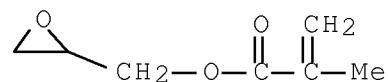
CM 1

CRN 155161-85-6  
CMF C13 H22 O8 S2

CM 2

CRN 2274-11-5  
CMF C8 H10 O4

CM 3

CRN 106-91-2  
CMF C7 H10 O3

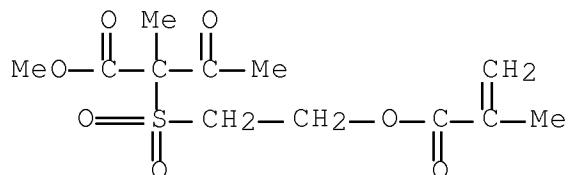
RN 155161-94-7 HCPLUS

CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with 2,3-dihydroxypropyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 155161-93-6

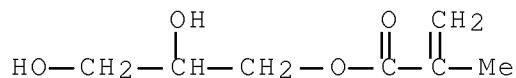
CMF C12 H18 O7 S



CM 2

CRN 5919-74-4

CMF C7 H12 O4



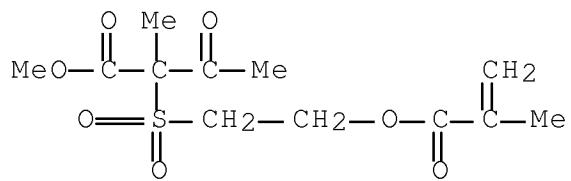
RN 155161-95-8 HCPLUS

CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with 2-[[2,2,2-trifluoro-1-(trifluoromethyl)ethoxy]carbonyl]amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

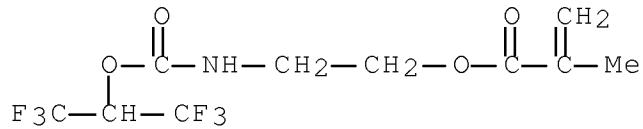
CRN 155161-93-6

CMF C12 H18 O7 S



CM 2

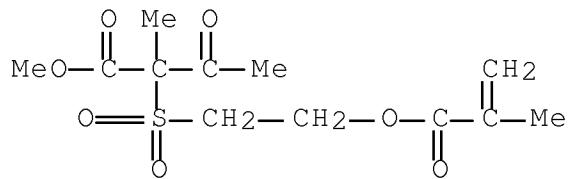
CRN 137130-28-0  
 CMF C10 H11 F6 N O4



RN 155161-96-9 HCAPLUS  
 CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

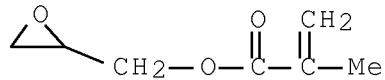
CM 1

CRN 155161-93-6  
 CMF C12 H18 O7 S



CM 2

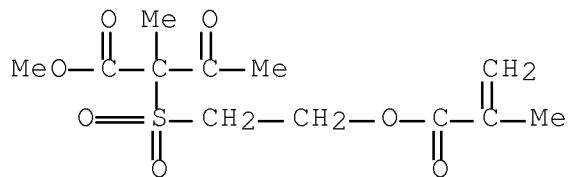
CRN 106-91-2  
 CMF C7 H10 O3



RN 155161-97-0 HCPLUS  
 CN Butanoic acid, 2-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]ethylsulfonyl-3-oxo-, methyl ester, polymer with 3-(dimethoxymethylsilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

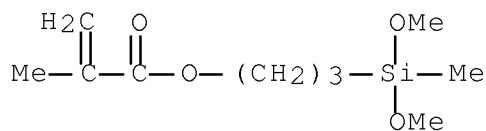
CM 1

CRN 155161-93-6  
 CMF C12 H18 O7 S



CM 2

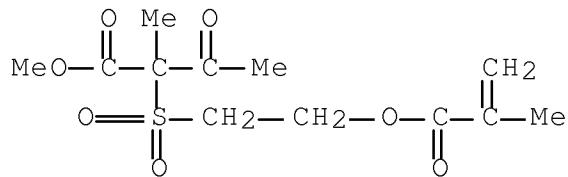
CRN 14513-34-9  
 CMF C10 H20 O4 Si



RN 155161-98-1 HCPLUS  
 CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with thiiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

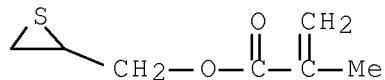
CM 1

CRN 155161-93-6  
 CMF C12 H18 O7 S



CM 2

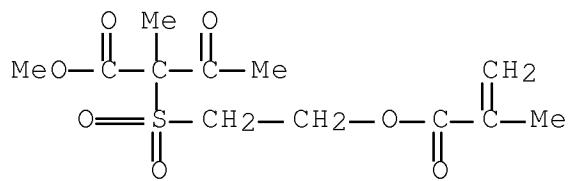
CRN 3139-91-1  
 CMF C7 H10 O2 S



RN 155161-99-2 HCPLUS  
 CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with ethenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

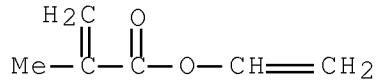
CRN 155161-93-6  
 CMF C12 H18 O7 S



CM 2

CRN 4245-37-8

CMF C6 H8 O2



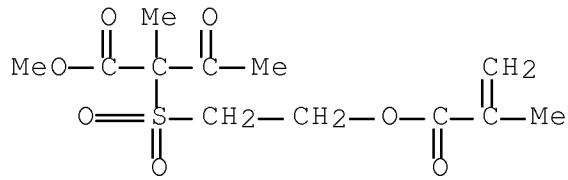
RN 155162-00-8 HCAPLUS

CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with dihydro-3-methylene-2,5-furandione (9CI) (CA INDEX NAME)

CM 1

CRN 155161-93-6

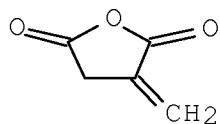
CMF C12 H18 O7 S



CM 2

CRN 2170-03-8

CMF C5 H4 O3



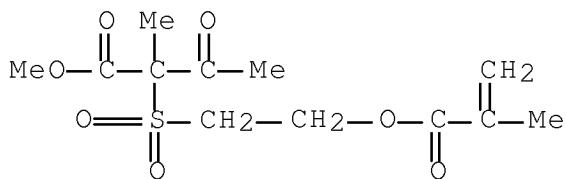
RN 155162-01-9 HCPLUS

CN Butanoic acid, 2-methyl-2-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, methyl ester, polymer with 6-(2,5-dihydro-3,4-dimethyl-2,5-dioxo-1H-pyrrol-1-yl)hexyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 155161-93-6

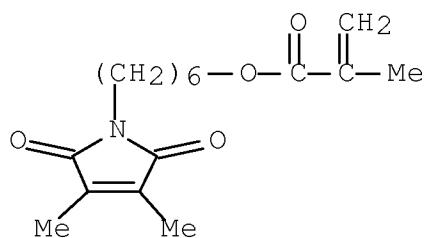
CMF C12 H18 O7 S



CM 2

CRN 63740-41-0

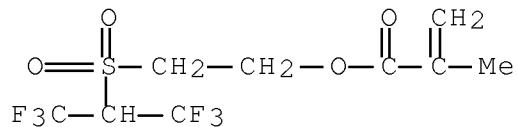
CMF C16 H23 N O4



RN 155162-03-1 HCPLUS  
 CN 2-Propenoic acid, 2-methyl-, oxiranylmethyl ester, polymer with  
 2-[2,2,2-trifluoro-1-(trifluoromethyl)ethyl]sulfonyl]ethyl  
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

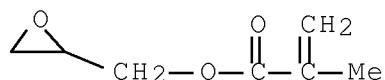
CM 1

CRN 155162-02-0  
 CMF C9 H10 F6 O4 S



CM 2

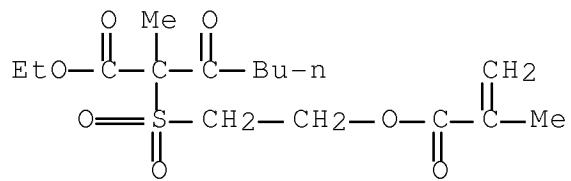
CRN 106-91-2  
 CMF C7 H10 O3



RN 155162-05-3 HCPLUS  
 CN Heptanoic acid, 2-methyl-2-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-3-oxo-, ethyl ester, polymer with  
 oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

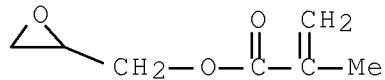
CRN 155162-04-2  
 CMF C16 H26 O7 S



CM 2

CRN 106-91-2

CMF C7 H10 O3



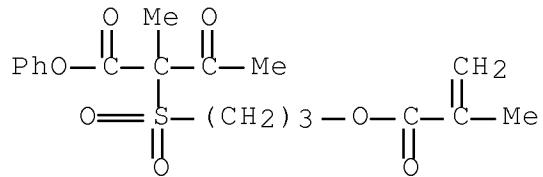
RN 155162-11-1 HCPLUS

CN Butanoic acid, 2-methyl-2-[[3-[(2-methyl-1-oxo-2-propenyl)oxyl]propyl]sulfonyl]-3-oxo-, phenyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 155162-10-0

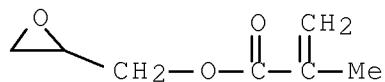
CMF C18 H22 O7 S



CM 2

CRN 106-91-2

CMF C7 H10 O3



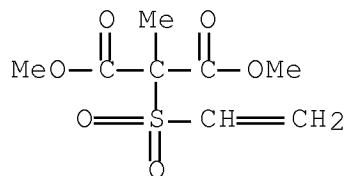
RN 155162-14-4 HCPLUS

CN Propanedioic acid, (ethenylsulfonyl)methyl-, dimethyl ester, polymer with methyl  $\alpha$ -methyl- $\alpha$ -[[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]sulfonyl]- $\beta$ -oxobenzenepropanoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 155162-13-3

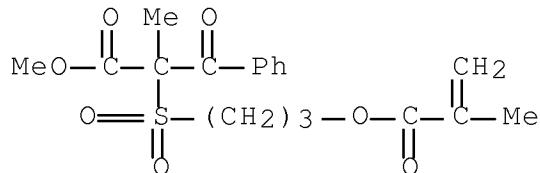
CMF C8 H12 O6 S



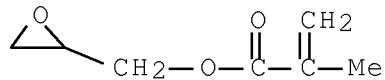
CM 2

CRN 155162-12-2

CMF C18 H22 O7 S

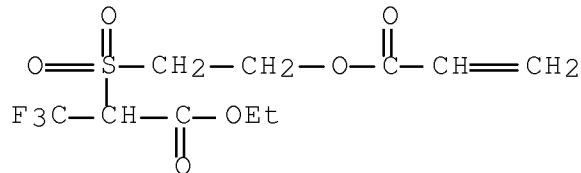


CM 3

CRN 106-91-2  
CMF C7 H10 O3

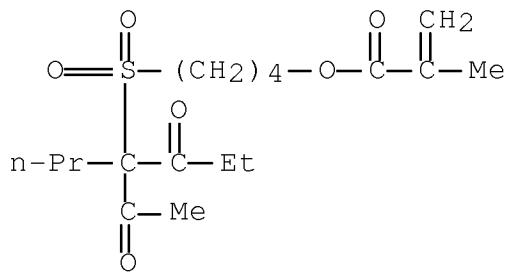
RN 155162-19-9 HCAPLUS  
 CN 2-Propenoic acid, 2-methyl-,  
 4-[(1-acetyl-2-oxo-1-propylbutyl)sulfonyl]butyl ester, polymer with  
 2-[(1-ethoxycarbonyl)-2,2,2-trifluoroethyl]sulfonyl]ethyl  
 2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA  
 INDEX NAME)

CM 1

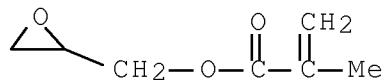
CRN 155162-18-8  
CMF C10 H13 F3 O6 S

CM 2

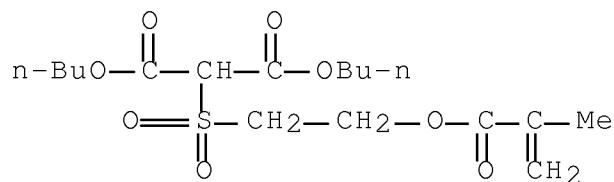
CRN 155162-17-7  
CMF C17 H28 O6 S



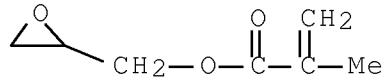
CM 3

CRN 106-91-2  
CMF C7 H10 O3RN 155162-21-3 HCAPLUS  
CN Propanedioic acid, [[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]-, dibutyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 155162-20-2  
CMF C17 H28 O8 S

CM 2

CRN 106-91-2  
CMF C7 H10 O3

L42 ANSWER 57 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1994:19283 HCAPLUS Full-text

DN 120:19283

OREF 120:3557a,3560a

TI Electrophotographic lithographic printing plate giving high sensitivity to semiconductor laser scanning method

IN Kato, Eiichi; Kasai, Kyosuke

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 75 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05034950	A	19930212	JP 1991-213050	19910731

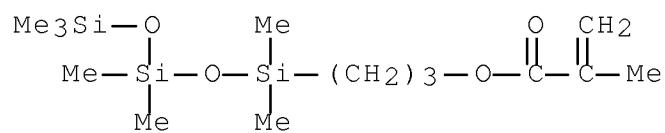
&lt;--

PRAI JP 1991-213050 19910731

AB In an electrophotog. lithog. printing plate having  $\geq 1$  photoconductor layer containing photoconductive ZnO, spectral sensitizing dye and binder resin, the photoconductor layer contains  $\geq 1$  kinds of binder resin (A) and  $\geq 1$  kinds of nonaq. dispersion resin particles (B) whose average grain diameter is smaller than or equal to the maximum grain diameter of the photoconductive ZnO particles. The binder resin (A) contains a repeating unit  $[a_1HC-Ca_2(COOR_3)]$  [ $a_1, 2 = H, \text{halo, cyano, hydrocarbon; } R_3 = \text{hydrocarbon}$ ] having weight average mol. weight 1,000-20,000 as a polymer component  $\geq 30\%$  and further contains  $\geq 1$  polar moiety selected from PO<sub>3</sub>H<sub>2</sub>, SO<sub>3</sub>H, COOH, P(:O)(OH)R<sub>1</sub> [ $R_1 = \text{hydrocarbon, } R_2 = \text{hydrocarbon}$ ], and a group containing a cyclic

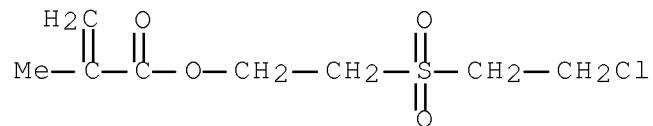
anhydride which terminates at least one end of the polymer backbone chain. The nonaq. dispersion resin particles (B) are made of a copolymer obtained by dispersion polymerization of a monofunctional monomer (C) with a monofunctional monomer (D) in the presence of a dispersion-stabilizing resin soluble in the nonaq. solvent, in which the monofunctional monomer (C) contains  $W_1(CH_2)n_1HC:CH_2$  and/or  $W_2(CH_2)n_2CH_2CH_2X$  [ $W_{1,2} = SO_2, CO, OCO$ ;  $n_1, n_2 = 0, 1$ ; and  $X = \text{halo}$ ] and is soluble in the nonaq. solvent but becoming insol. upon polymerization and the monofunctional monomer (D) contains a substituent containing Si and/or F.

IC ICM G03G005-05  
 ICS G03G005-05; G03G005-06; G03G005-08; G03G013-28  
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 IT 151752-85-1P  
 RL: PREP (Preparation)  
 (preparation and use of , electrophotog. lithog. printing plate  
 from)  
 IT 149839-06-5DP, polymers with methacrylates 151733-27-6P  
 151733-28-7P 151733-29-8P 151733-30-1P 151733-31-2P  
 151733-32-3P 151733-33-4P 151733-34-5P 151733-35-6P  
 151735-81-8P 151752-65-7P 151752-80-6P  
 151752-81-7P 151752-82-8P 151752-83-9P  
 151752-84-0P 151758-71-3P 151758-72-4P 151758-73-5P  
 151758-74-6P 151758-75-7P 151758-76-8P 151758-77-9P  
 151758-79-1P 151758-81-5P 151758-82-6P 151758-83-7P  
 151758-84-8P 151767-53-2P 151767-55-4P 151813-66-0P  
 151813-68-2P 151835-58-4P  
 RL: SPN (Synthetic preparation); PREP (Preparation)  
 (preparation and use of of, electrophotog. lithog. printing plate  
 from)  
 IT 151752-85-1P  
 RL: PREP (Preparation)  
 (preparation and use of , electrophotog. lithog. printing plate  
 from)  
 RN 151752-85-1 HCPLUS  
 CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with  
 2-[(2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
 1,2-ethanediyl di-2-propenoate, 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate,  
 graft (9CI) (CA INDEX NAME)  
 CM 1  
 CRN 150624-86-5  
 CMF C14 H32 O4 Si3



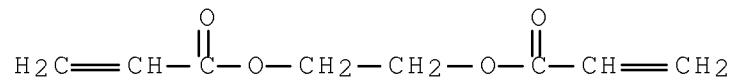
CM 2

CRN 143131-91-3  
 CMF C8 H13 Cl O4 S



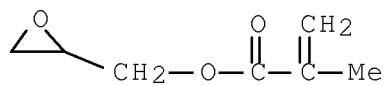
CM 3

CRN 2274-11-5  
 CMF C8 H10 O4

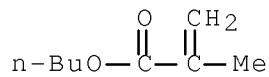


CM 4

CRN 106-91-2  
 CMF C7 H10 O3



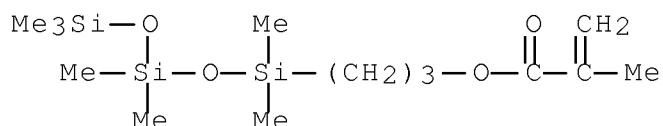
CM 5

CRN 97-88-1  
CMF C8 H14 O2IT 151733-35-6P 151752-80-6P 151752-81-7P  
151752-82-8P 151752-83-9P 151752-84-0P  
151758-77-9P 151758-84-8P 151835-58-4PRL: SPN (Synthetic preparation); PREP (Preparation)  
(preparation and use of of, electrophotog. lithog. printing plate  
from)

RN 151733-35-6 HCPLUS

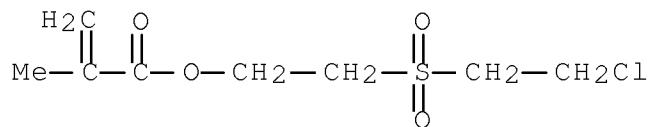
CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester,  
polymer with 1,2-ethanediyl di-2-propenoate,  
3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate, methyl  
2-methyl-2-propenoate and methyl 2-propenoate, graft (9CI) (CA  
INDEX NAME)

CM 1

CRN 150624-86-5  
CMF C14 H32 O4 Si3

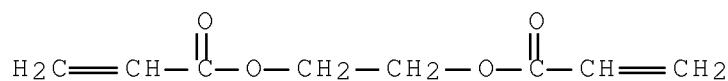
CM 2

CRN 143131-91-3  
CMF C8 H13 C1 O4 S



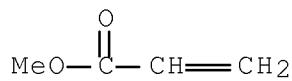
CM 3

CRN 2274-11-5  
CMF C8 H10 O4



CM 4

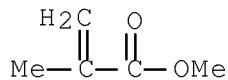
CRN 96-33-3  
CMF C4 H6 02



CM 5

CRN 80-62-6

CMF C5 H8 O2



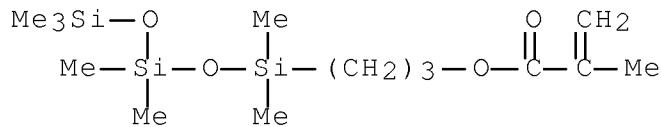
RN 151752-80-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester,  
 polymer with 1,2-ethanediyl di-2-propenoate,  
 3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate and pentyl  
 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 150624-86-5

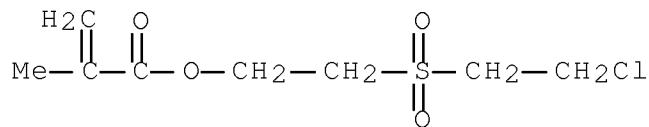
CMF C14 H32 O4 Si3



CM 2

CRN 143131-91-3

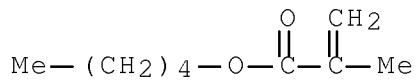
CMF C8 H13 Cl O4 S



CM 3

CRN 2849-98-1

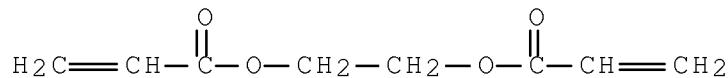
CMF C9 H16 O2



CM 4

CRN 2274-11-5

CMF C8 H10 O4



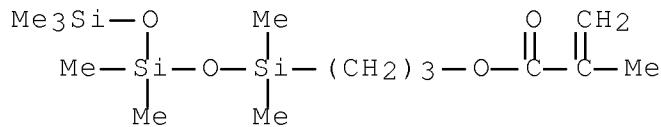
RN 151752-81-7 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with  
 2-[ (2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
 1,2-ethanediyl di-2-propenoate, 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate and 2-propenamide, graft (9CI) (CA INDEX  
 NAME)

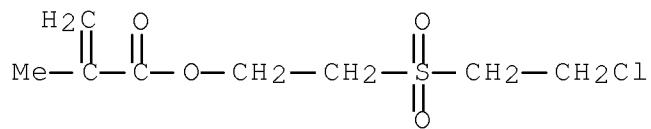
CM 1

CRN 150624-86-5

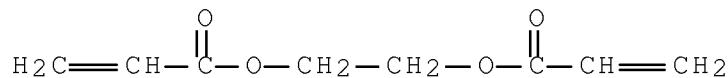
CMF C14 H32 O4 Si3



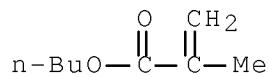
CM 2

CRN 143131-91-3  
CMF C8 H13 Cl O4 S

CM 3

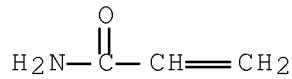
CRN 2274-11-5  
CMF C8 H10 O4

CM 4

CRN 97-88-1  
CMF C8 H14 O2

CM 5

CRN 79-06-1  
CMF C3 H5 N O



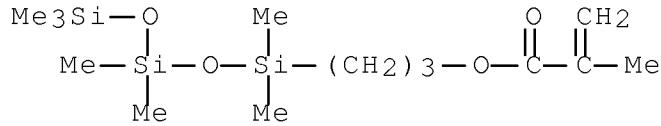
RN 151752-82-8 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with  
 2-[ (2-chloroethyl) sulfonyl]ethyl 2-methyl-2-propenoate,  
 1,2-ethanediyl di-2-propenoate and 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 150624-86-5

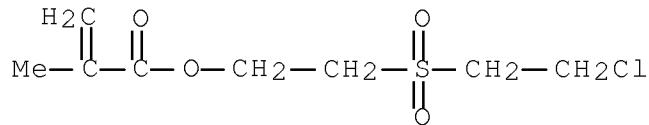
CMF C14 H32 O4 Si3



CM 2

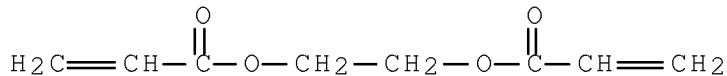
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CMF C8 H13 Cl O4 S



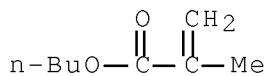
CM 3

CRN 2274-11-5  
 CMF C8 H10 O4



CM 4

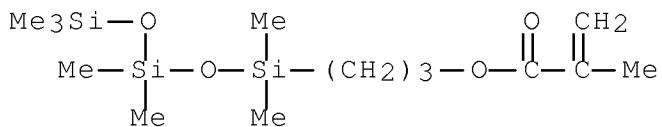
CRN 97-88-1  
 CMF C8 H14 O2



RN 151752-83-9 HCAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester, polymer with butyl 2-propenoate, 1,2-ethanediyl di-2-propenoate, 3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

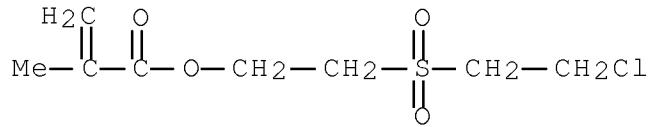
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 CMF C14 H32 O4 Si3



CM 2

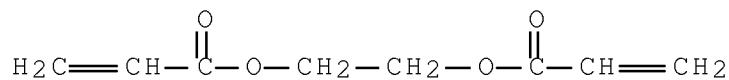
10/535,333

CRN 143131-91-3  
CMF C8 H13 Cl O4 S



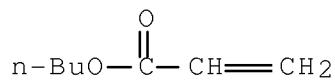
CM 3

CRN 2274-11-5  
CMF C8 H10 O4



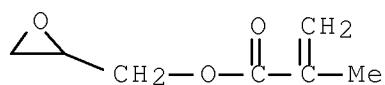
CM 4

CRN 141-32-2  
CMF C7 H12 O2



CM 5

CRN 106-91-2  
CMF C7 H10 O3



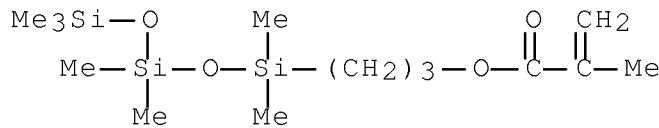
RN 151752-84-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester,  
 polymer with 1,2-ethanediyl di-2-propenoate, ethyl  
 2-methyl-2-propenoate and 3-(heptamethyltrisiloxanyl)propyl  
 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 150624-86-5

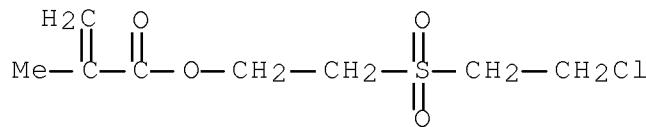
CMF C14 H32 O4 Si3



CM 2

CRN 143131-91-3

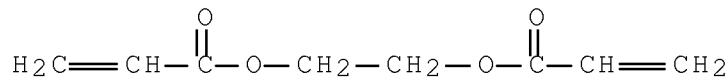
CMF C8 H13 Cl O4 S



CM 3

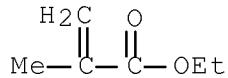
CRN 2274-11-5

CMF C8 H10 O4



CM 4

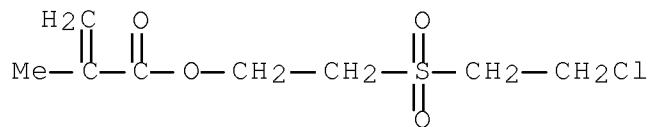
CRN 97-63-2  
 CMF C6 H10 O2



RN 151758-77-9 HCPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with  
 2-[ (2-chloroethyl)sulfonyl]ethyl 2-methyl-2-propenoate,  
 2,2,3,4,4,4-hexafluorobutyl 2-methyl-2-propenoate, hexyl  
 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate,  
 graft (9CI) (CA INDEX NAME)

CM 1

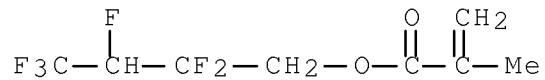
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CM 2

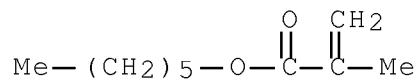
10/535,333

CRN 36405-47-7  
CMF C8 H8 F6 O2



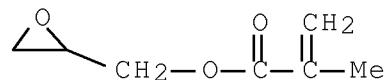
CM 3

CRN 142-09-6  
CMF C10 H18 O2



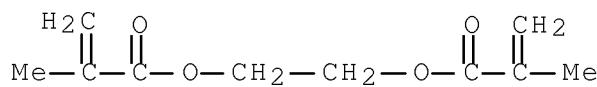
CM 4

CRN 106-91-2  
CMF C7 H10 O3



CM 5

CRN 97-90-5  
CMF C10 H14 O4



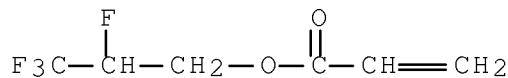
RN 151758-84-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with  
 3-[(2-chloroethyl)sulfonyl]propyl 2-methyl-2-propenoate, hexyl  
 2-methyl-2-propenoate, oxiranylmethyl 2-methyl-2-propenoate and  
 2,3,3,3-tetrafluoropropyl 2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 147987-23-3

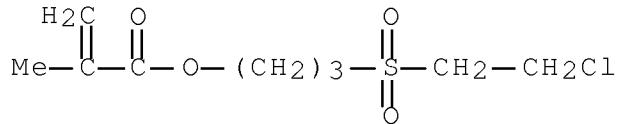
CMF C6 H6 F4 O2



CM 2

CRN 140913-31-1

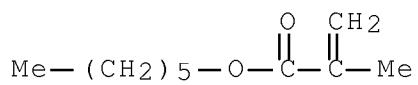
CMF C9 H15 Cl O4 S



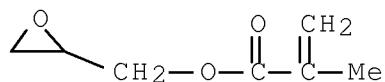
CM 3

CRN 142-09-6

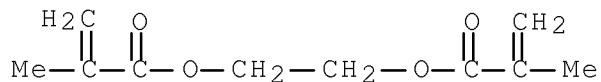
CMF C10 H18 O2



CM 4

CRN 106-91-2  
CMF C7 H10 O3

CM 5

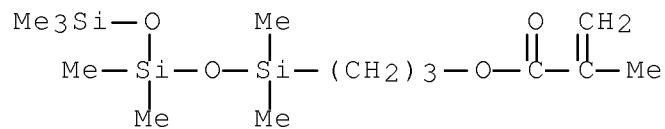
CRN 97-90-5  
CMF C10 H14 O4

RN 151835-58-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(2-chloroethyl)sulfonyl]ethyl ester, polymer with dodecyl 2-methyl-2-propenoate polymer with oxiranylmethyl 2-methyl-2-propenoate 2-methyl-2-propenoate, 1,2-ethanediyl di-2-propenoate and 3-(heptamethyltrisiloxanyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

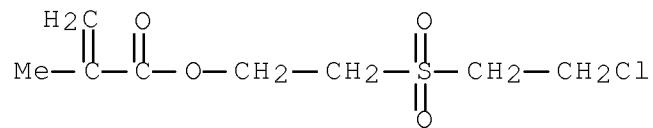
CM 1

CRN 150624-86-5  
CMF C14 H32 O4 Si3



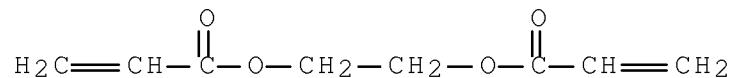
CM 2

CRN 143131-91-3  
 CMF C8 H13 Cl O4 S



CM 3

CRN 2274-11-5  
 CMF C8 H10 O4

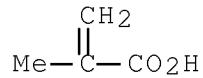


CM 4

CRN 52229-66-0  
 CMF (C16 H30 O2 . C7 H10 O3)x . x C4 H6 O2

CM 5

CRN 79-41-4  
 CMF C4 H6 O2

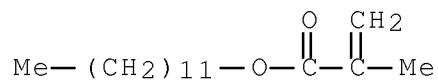


CM 6

CRN 28851-51-6  
 CMF (C16 H30 O2 . C7 H10 O3)x  
 CCI PMS

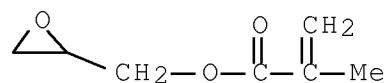
CM 7

CRN 142-90-5  
 CMF C16 H30 O2



CM 8

CRN 106-91-2  
 CMF C7 H10 O3



AN 1992:224643 HCAPLUS Full-text  
 DN 116:224643  
 OREF 116:37865a,37868a

TI Electrophotographic lithographic printing plate precursor with improved hydrophilic properties

IN Kato, Eiichi; Oda, Akio; Kasai, Seishi

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 65 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 425224	A1	19910502	EP 1990-311568	199010 22
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	R: DE, GB				
	JP 03139653	A	19910613	JP 1989-277217	198910 26
					<--
	JP 03168764	A	19910722	JP 1989-307742	198911 29
					<--

PRAI JP 1989-277217 A 19891026  
 JP 1989-307742 A 19891129

AB The title precursor, which has improved hydrophilic properties, is storage stable, and can be readily made hydrophilic under a short-time processing regime, uses a conductive support having  $\geq 1$  photoconductive layer and an outermost surface layer containing  $\geq 1$  resin containing  $\geq 1$  polymeric component with  $\geq 1$  functional group of the formula  $W_1(CH_2)_mCH:CH_2$  and  $W_2(CH_2)_nCH_2CH_2X$  ( $W_1, W_2 = SO_2, CO, O_2C$ ;  $m$  and  $n = 0$  or  $1$ ;  $X =$  a halogen). Thus, an In oxide-coated PET support was overcoated with an organic photoconductive composition and then with a solution of a 2-hydroxyethyl methacrylate-propenoylemethyl methacrylate polymer. The resultant precursor was then exposed and processed to give a lithog. plate showing excellent hydrophilic properties.

IC ICM G03G005-147

ICS G03G013-28

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 40081-37-6P 51939-26-5P 127568-58-5P 139252-83-8P

139289-41-1P	140913-02-6P	140913-03-7P	140913-04-8P
140913-06-0P	140913-08-2P	140913-10-6P	140913-12-8P
140913-14-0P	140913-16-2P	140913-17-3P	140913-18-4P
140913-19-5P	140913-20-8P	140913-21-9P	140913-22-0P
140913-23-1P	140913-24-2P	140913-25-3P	140913-26-4P
140913-27-5P	140913-30-0P	140913-33-3P	140913-35-5P
140913-37-7P	140913-38-8P	140913-51-5P	140913-52-6P
140913-54-8P			

RL: PREP (Preparation)

(preparation and electrophotog. lithog. plate precursors with surface

layer containing, for improved hydrophilicity)

IT 140913-29-7P 140913-32-2P 140913-34-4P 140913-39-9DP,  
 dehydrobrominated 140913-39-9P 140913-40-2P 140913-42-4DP,  
 dehydrochlorinated 140913-43-5P 140913-44-6P 140913-45-7P  
 140913-46-8P 140913-47-9P 140913-48-0P 140913-49-1P  
 140913-50-4P 140936-82-9P 141078-86-6P

RL: PREP (Preparation)

(preparation of, for electrophotog. lithog. plate precursors with improved hydrophilicity)

IT 140913-14-0P

RL: PREP (Preparation)

(preparation and electrophotog. lithog. plate precursors with surface

layer containing, for improved hydrophilicity)

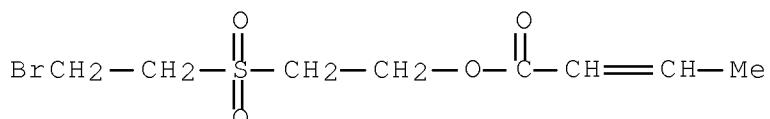
RN 140913-14-0 HCAPLUS

CN 2-Butenoic acid, 2-[(2-bromoethyl)sulfonyl]ethyl ester, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 140913-13-9

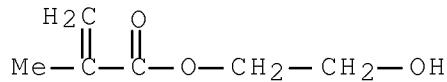
CMF C8 H13 Br O4 S



CM 2

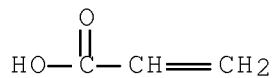
10/535,333

CRN 868-77-9  
CMF C6 H10 O3



CM 3

CRN 79-10-7  
CMF C3 H4 O2



IT 140913-32-2P

RL: PREP (Preparation)

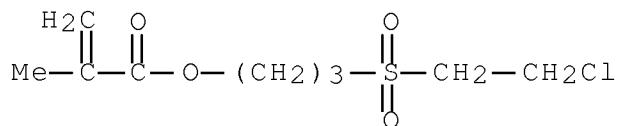
(preparation of, for electrophotog. lithog. plate precursors with improved hydrophilicity)

RN 140913-32-2 HCPLUS

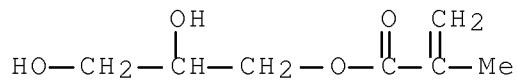
CN 2-Propenoic acid, 2-methyl-, 3-[(2-chloroethyl)sulfonyl]propyl ester, polymer with 2,3-dihydroxypropyl 2-methyl-2-propenoate (9CI)  
(CA INDEX NAME)

CM 1

CRN 140913-31-1  
CMF C9 H15 Cl O4 S



CM 2

CRN 5919-74-4  
CMF C7 H12 O4

L42 ANSWER 63 OF 65 HCPLUS COPYRIGHT 2008 ACS on STN  
 AN 1989:125237 HCPLUS Full-text  
 DN 110:125237  
 OREF 110:20489a,20492a  
 TI Color photographic material containing polymeric coupler incorporating group crosslinking gelatin  
 IN Sakanoue, Kei; Ishii, Yoshio; Hirano, Tsumoru  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 204 pp.  
 CODEN: EPXXDW

DT Patent  
 LA English  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 280330	A2	19880831	EP 1988-102925	198802 26
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	EP 280330	A3	19890920		
	EP 280330	B1	19930721		
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19901002

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198802

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A

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JP 1987-44792

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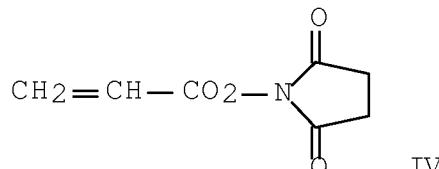
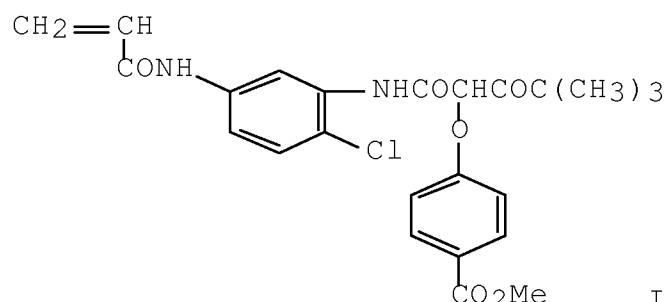
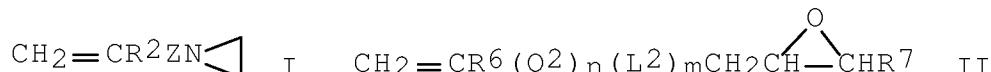
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JP 1987-315766

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19871214

GI



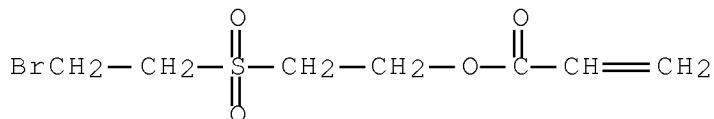
AB The title H<sub>2</sub>O-soluble coupler contains a vinyl monomer having a color coupler moiety and  $\geq 1$  monomer selected from monomers of the formula:  $\text{CH}_2:\text{CR}^1(\text{L})\text{kX}$  [R<sub>1</sub> = H, C<sub>1</sub>-6 alkyl, Cl; L = C<sub>1</sub>-20 divalent group; k = 0, 1; X = active ester group], I [R<sub>2</sub> = H, Cl, alkyl; Z = CO, NHCO, CO<sub>2</sub>R<sub>3</sub>; R<sub>3</sub> = alkylene],  $\text{CH}_2:\text{CR}^4\text{Q}^1\text{L}^1\text{SO}_2\text{R}^5$  [R<sub>4</sub> = H, C<sub>1</sub>-6 alkyl; Q<sub>1</sub> = CO<sub>2</sub>, CONR<sub>1</sub>, C<sub>6</sub>-10 arylene; L<sub>1</sub> = divalent group; R<sub>5</sub> = CH:CH<sub>2</sub>, CH<sub>2</sub>CH<sub>2</sub>X; X = group capable of being substituted by a nucleophilic group or being released by a base in the form of HX]; II [R<sub>6</sub> = R<sub>2</sub>; Q<sub>2</sub> = CO<sub>2</sub>, CONR<sub>2</sub>, C<sub>6</sub>-10 arylene; L<sub>2</sub> = L<sub>1</sub>; R<sub>7</sub> = H, alkyl; m, n = 0 or 1; and m and n are not 0 at the same time]. The coupler has excellent diffusion resistance, provides a sufficiently high image d., and has a rapid rate of crosslinking with gelatin. The photog. material has excellent layer strength and image sharpness. Thus, a III-IV-Na

methacrylate copolymer was prepared and used as a yellow coupler in a photog. film. The coupler had excellent diffusion resistance.

IC ICM G03C007-32  
 ICA C08F222-38  
 CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 Section cross-reference(s): 38  
 IT 118038-12-3P 118038-15-6P 118038-16-7P 118038-42-9P  
 118065-91-1P 118066-09-4P 118066-11-8P 118110-88-6P  
 RL: SPN (Synthetic preparation); PREP (Preparation)  
 (preparation and use of, as photog. yellow coupler with excellent diffusion resistance)  
 IT 118038-15-6P  
 RL: SPN (Synthetic preparation); PREP (Preparation)  
 (preparation and use of, as photog. yellow coupler with excellent diffusion resistance)  
 RN 118038-15-6 HCPLUS  
 CN  $\beta$ -Alanine, N-(2-methyl-1-oxo-2-propenyl)-, polymer with 2-[(2-bromoethyl)sulfonyl]ethyl 2-propenoate and N-[2-chloro-5-[(2-methyl-1-oxo-2-propenyl)amino]phenyl]-2-[4-[(4-hydroxyphenyl)sulfonyl]phenoxy]-4,4-dimethyl-3-oxopentanamide (9CI) (CA INDEX NAME)

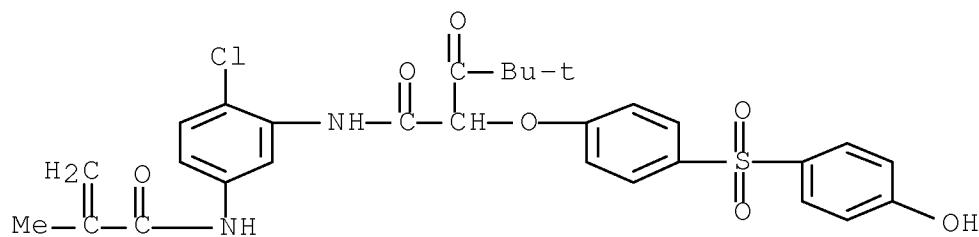
CM 1

CRN 118038-14-5  
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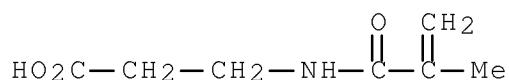


CM 2

CRN 118038-13-4  
 CMF C29 H29 Cl N2 O7 S



CM 3

CRN 59178-90-4  
CMF C7 H11 N O3

L42 ANSWER 65 OF 65 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1971:42849 HCAPLUS Full-text

DN 74:42849

OREF 74:6901a,6904a

TI Polymerizable bis(perfluoroalkylsulfonyl)methanes

IN Koshar, Robert J.

PA Minnesota Mining and Manufacturing Co.

SO Ger. Offen., 24 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2012011	A	19701126	DE 1970-2012011	197003 13
US	3704311	A	19721128	US 1969-807408	196903

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FR 2038947	A5	19710108	FR 1970-9195	197003 13
GB 1309013	A	19730307	GB 1971-12309	197003 13
CH 551954	A	19740731	CH 1970-3837	197003 13
CA 962693	A1	19750211	CA 1970-77438	197003 13
JP 48026742	B	19730815	JP 1970-21246	197003 14
US 3758593	A	19730911	US 1972-248900	197205 01
US 3758591	A	19730911	US 1972-249116	197205 01
US 3758592	A	19730911	US 1972-249117	197205 01
US 3758531	A	19730911	US 1972-249244	197205 01
PRAI US 1969-807408	A	19690314		

AB The title compds. are prepared by conventional methods, including treating bis(perfluoroalkylsulfonyl)methanes with organomagnesium halides and then with unsatd. bromides or with Br followed by reactive derivs. of unsatd. compds. Thus, 25 g bis(perfluoroctylsulfonyl)methane in 125 ml THF was treated with 14 ml 3M MeMgCl in THF, stirred 1 hr at room temperature, treated with 5.1 g allyl bromide, stirred 1 hr at 60°, cooled to 0°, and hydrolyzed to give 8.7 g 4,4-bis(perfluoroctylsulfonyl)-1-butene.

3,3-Bis(trifluoromethylsulfonyl)-1-propanol was prepared by treating  $(CF_3SO_2)_2CH_2$  first with  $MeMgBr$  and then with ethylene oxide. Treating  $(F_3CSO_2)_2CHK$  with Cl gave  $(F_3CSO_2)_2CHCl$ , which was suitable for use as a catalyst in the cationic polymerization of epoxides. The unsatd. compds. are useful in the preparation of ion exchange resins.

IC C07C069-54

CC 35 (Synthetic High Polymers)

IT 29214-36-6P 29269-32-7P 30350-16-4P 30354-24-6P  
 30354-26-8P 30354-27-9P 30354-36-0P 30354-37-1P 30354-38-2P  
 30354-40-6P 30354-41-7P 30354-42-8P 30416-74-1P 30416-80-9P  
 30416-81-0P 30416-82-1P 60875-58-3P, Methane,  
 bromobis[(trifluoromethyl)sulfonyl]-, ion(1-), silver(1+)

RL: PREP (Preparation)  
 (preparation of)

IT 30350-16-4P

RL: PREP (Preparation)  
 (preparation of)

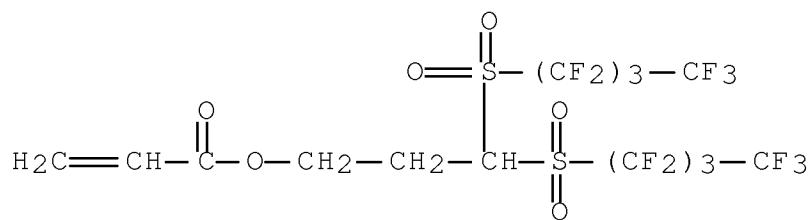
RN 30350-16-4 HCPLUS

CN Acrylic acid, 3,3-bis[(nonafluorobutyl)sulfonyl]propyl ester,  
 polymers (8CI) (CA INDEX NAME)

CM 1

CRN 29214-38-8

CMF C14 H8 F18 O6 S2



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